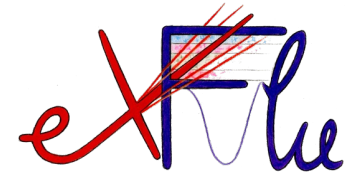




AIDAInnova 2nd Annual Meeting
24–27 April 2023
Valencia, Spain



Thin Silicon Sensors for Extreme Fluences eXFlu-innova

V. Sola, Torino University and INFN – Torino Unit

F. Moscatelli, CNR–IOM and INFN – Perugia Unit

G. Paternoster, FBK – SD



The Team

R. Arcidiacono, N. Cartiglia, M. Costa, M. Ferrero, S. Galletto, S. Giordanengo,
L. Lanteri, L. Menzio, R. Mulargia, N. Pastrone, F. Siviero, VS
INFN Torino, Università degli Studi di Torino, Università del Piemonte Orientale

P. Asenov, T. Croci, A. Fondacci, A. Morozzi, D. Passeri, FM
INFN Perugia , Università degli Studi di Perugia, CNR-IOM

M. Boscardin, M. Centis Vignali, F. Ficorella, O. Hammad Alì, GP
G. Borghi*
Fondazione Bruno Kessler, TIFPA
* now at Politecnico di Milano

A new Sensor Design

Goal: Design planar silicon sensors able to work in the fluence range $10^{16} - 10^{17} n_{eq}/cm^2$

Difficult to operate silicon sensors above $10^{16} n_{eq}/cm^2$ due to:

- defects in the silicon lattice structure → increase of the dark current
- trapping of the charge carriers → decrease of the charge collection efficiency
- change in the bulk effective doping → impossible to fully deplete the sensors

The ingredients to overcome the present limits above $10^{16} n_{eq}/cm^2$ are:

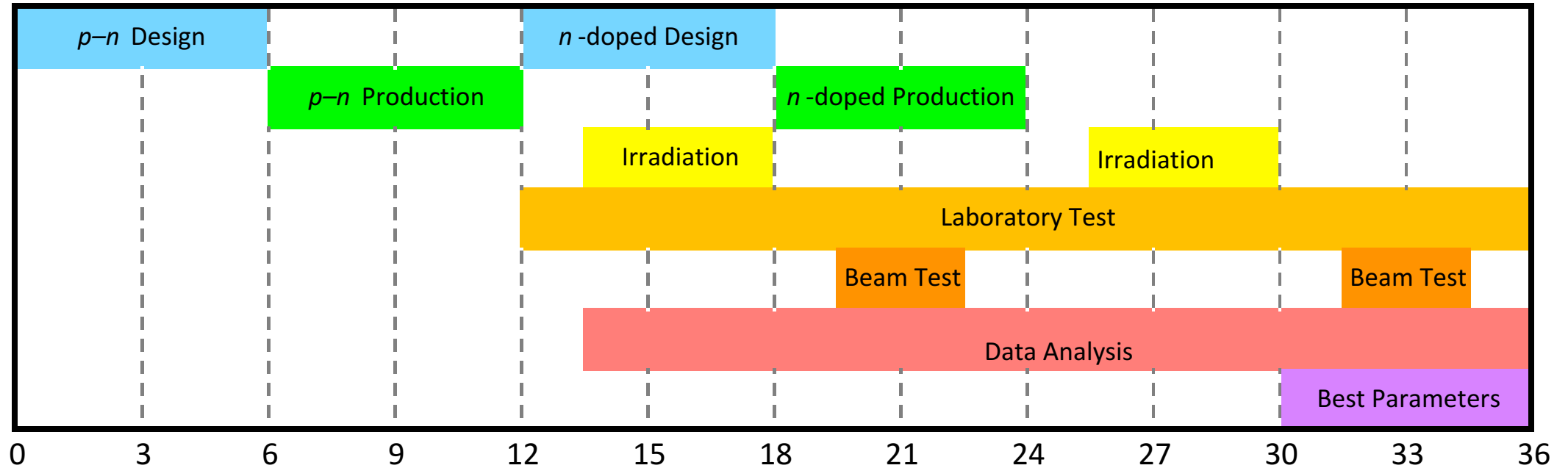
1. **saturation** of the radiation damage effects above $5 \cdot 10^{15} n_{eq}/cm^2$
2. the use of **thin** active substrates (15 – 45 μm) with **internal gain**
3. **extension** of the charge carrier multiplication up to $10^{17} n_{eq}/cm^2$ → **Compensated LGADs**

Project Activities

The activities of the proposal concentrate on the realisation of the most innovative part of our design, **the compensated gain layer**

- ▷ Two sensor productions will be performed, one to manufacture the **first compensated LGADs** and one to study the **donor removal**
- ▷ The production **process flows will be simulated**, to optimise the procedures and sequences of implantation and activation of dopants
- ▷ Both productions will be **tested before and after irradiation** to measure the initial donor removal and the performances of compensated LGADs

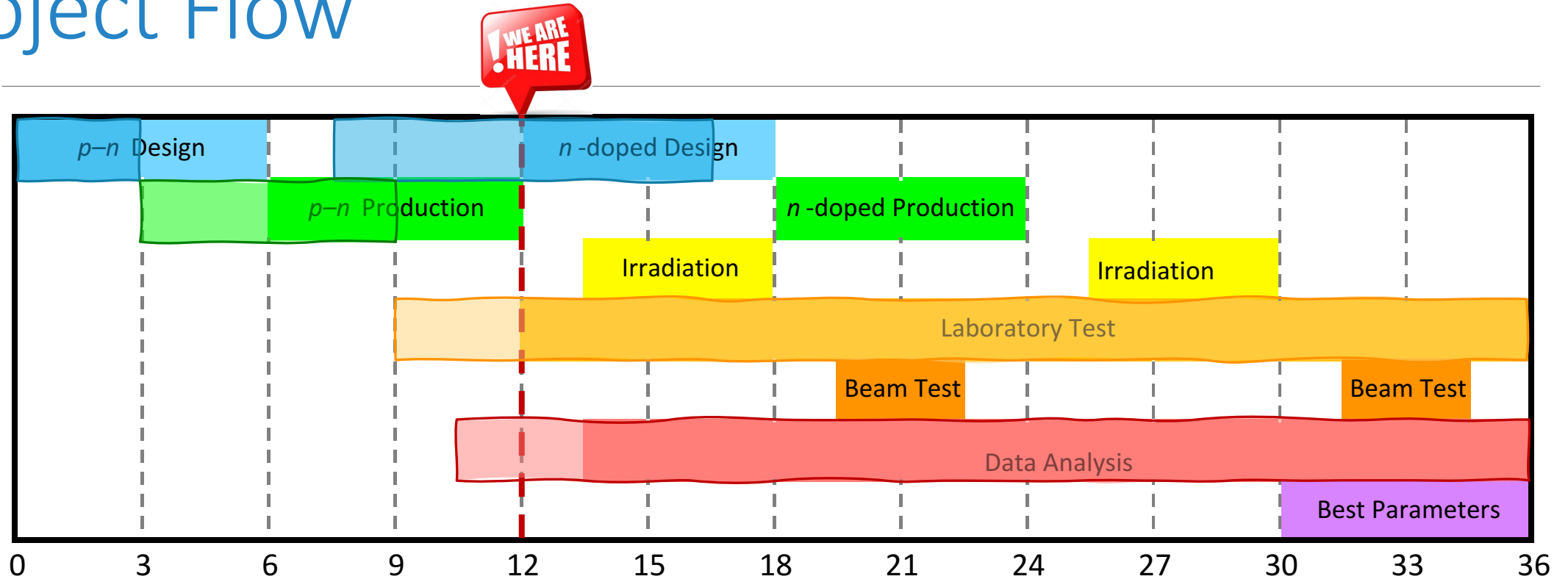
Project Flow




Deliverables:

1. **simulation and design** of the $p-n$ compensated gain implant (M6)
2. **production** of $p-n$ compensated sensors and n -doped sensors (M12 & M24)
3. **identifications of the best parameters** to manufacture compensated LGADs (M36)

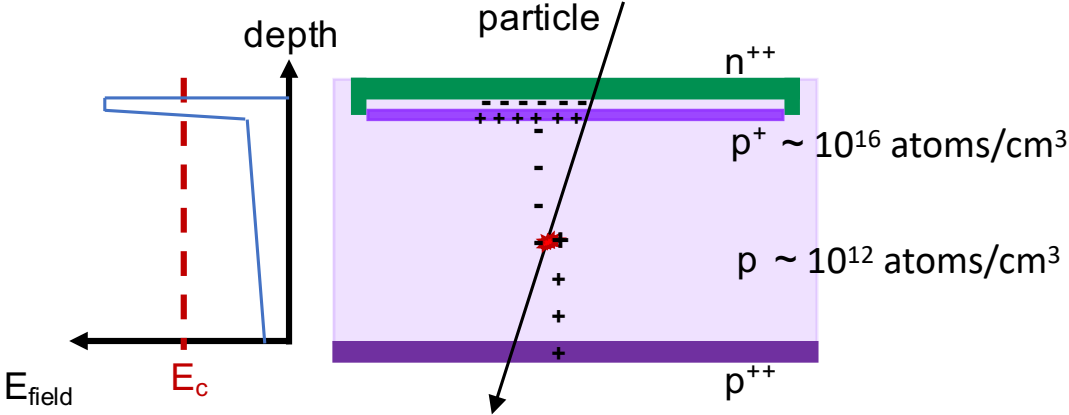
Project Flow



Deliverables:

1. **simulation and design** of the $p-n$ compensated gain implant (M6) – DONE
2. **production** of $p-n$ compensated sensors (M12) – DONE and n -doped sensors (M24) – 
3. **identifications of the best parameters** to manufacture compensated LGADs (M36) – pending

Sensors for Extreme Fluences – Recap

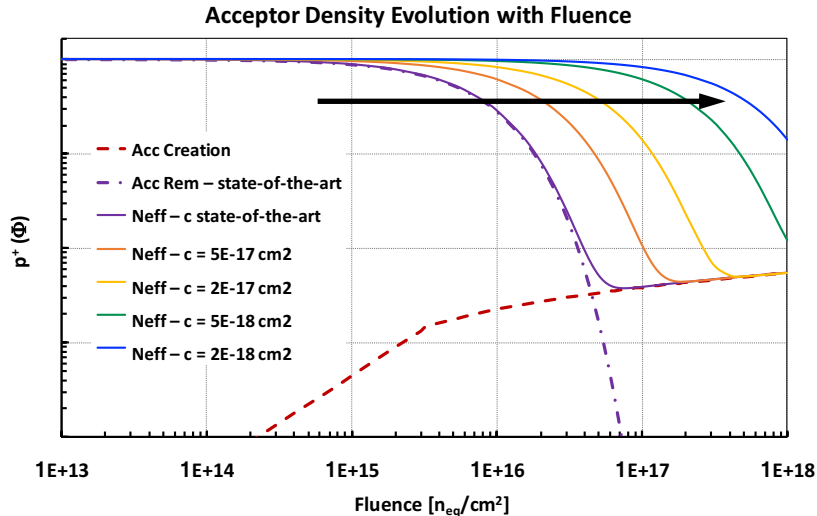
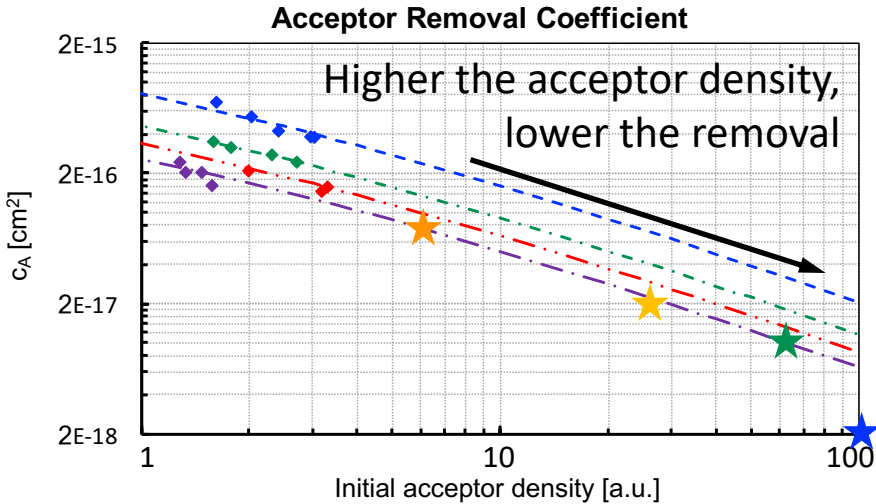


The acceptor removal mechanism deactivates the p^+ -doping of the **gain layer** with irradiation according to

$$p^+(\Phi) = p^+(0) \cdot e^{-c_A \Phi}$$

where c_A is the acceptor removal coefficient

c_A depends on the initial acceptor density, $p^+(0)$, and on the defect engineering of the gain layer atoms



Lowering c_A extends the gain layer survival up to the highest fluences

→ **compensation**

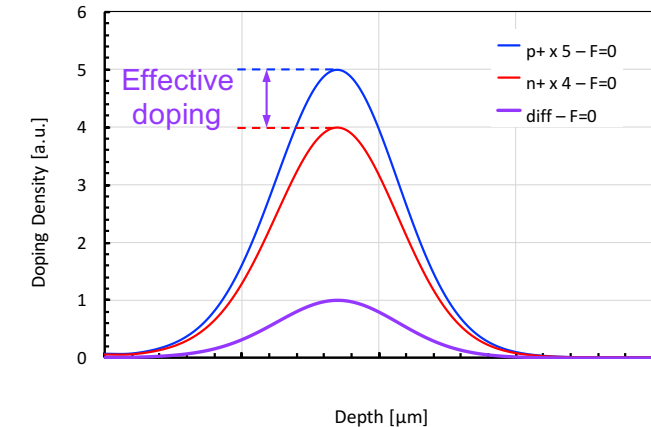
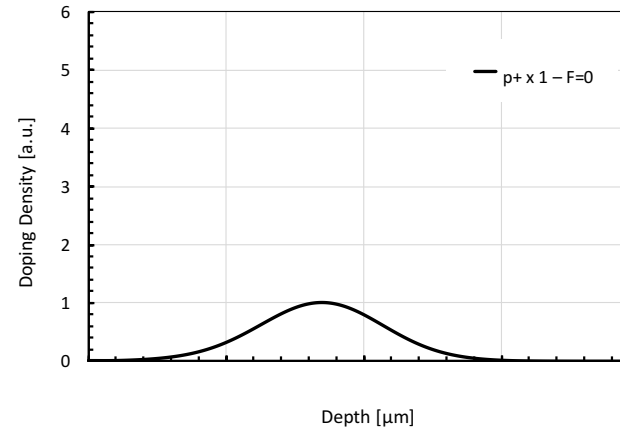
Compensation at a Glance

Impossible to reach the design target with the present design of the gain layer

Use the interplay between acceptor and donor removal to keep a constant gain layer active doping density

Many unknown:

- ▷ donor removal coefficient, from $n^+(\Phi) = n^+(0) \cdot e^{-c_D \Phi}$
- ▷ interplay between donor and acceptor removal (c_D vs c_A)
- ▷ effects of substrate impurities on the removal coefficients

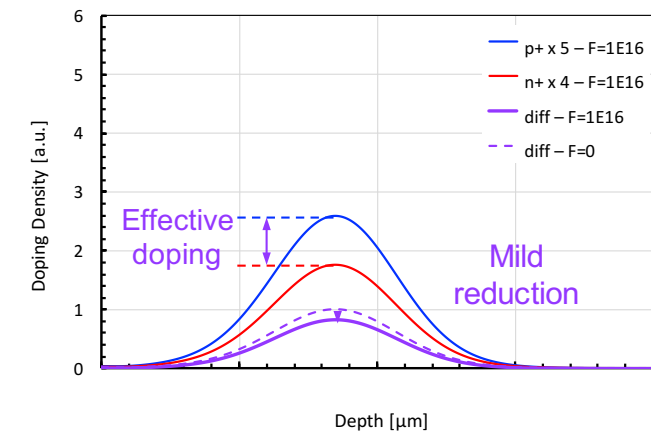
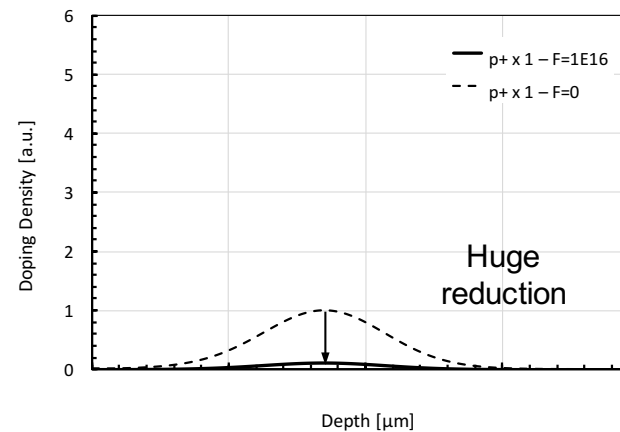


Depth [μm]

Depth [μm]



Irradiation
 $\Phi = 1\text{E}16 \text{ cm}^{-2}$



Depth [μm]

Depth [μm]

Standard LAGD design

Compensated LAGD design

The EXFLU1 Production Batch at a Glance

**A batch of thin LGAD for extreme fluences was released by the FBK foundry
⇒ EXFLU1**

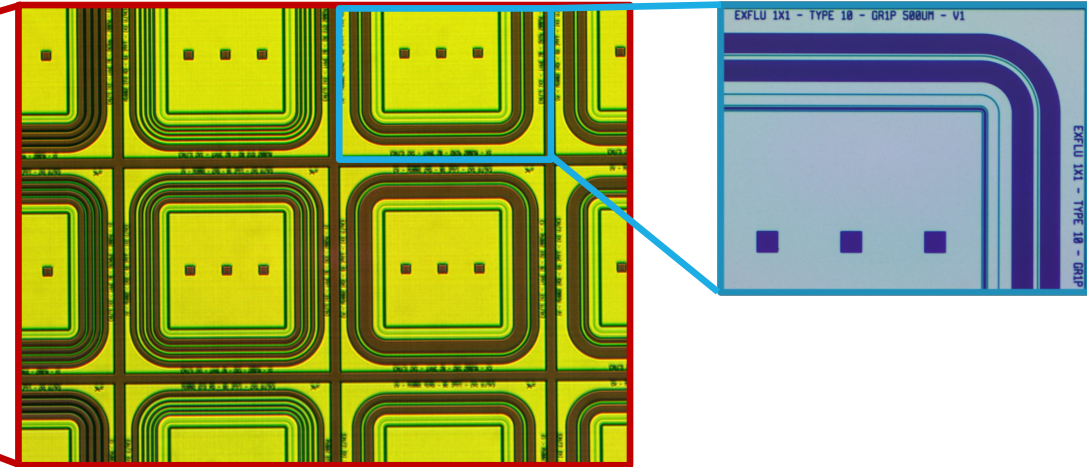
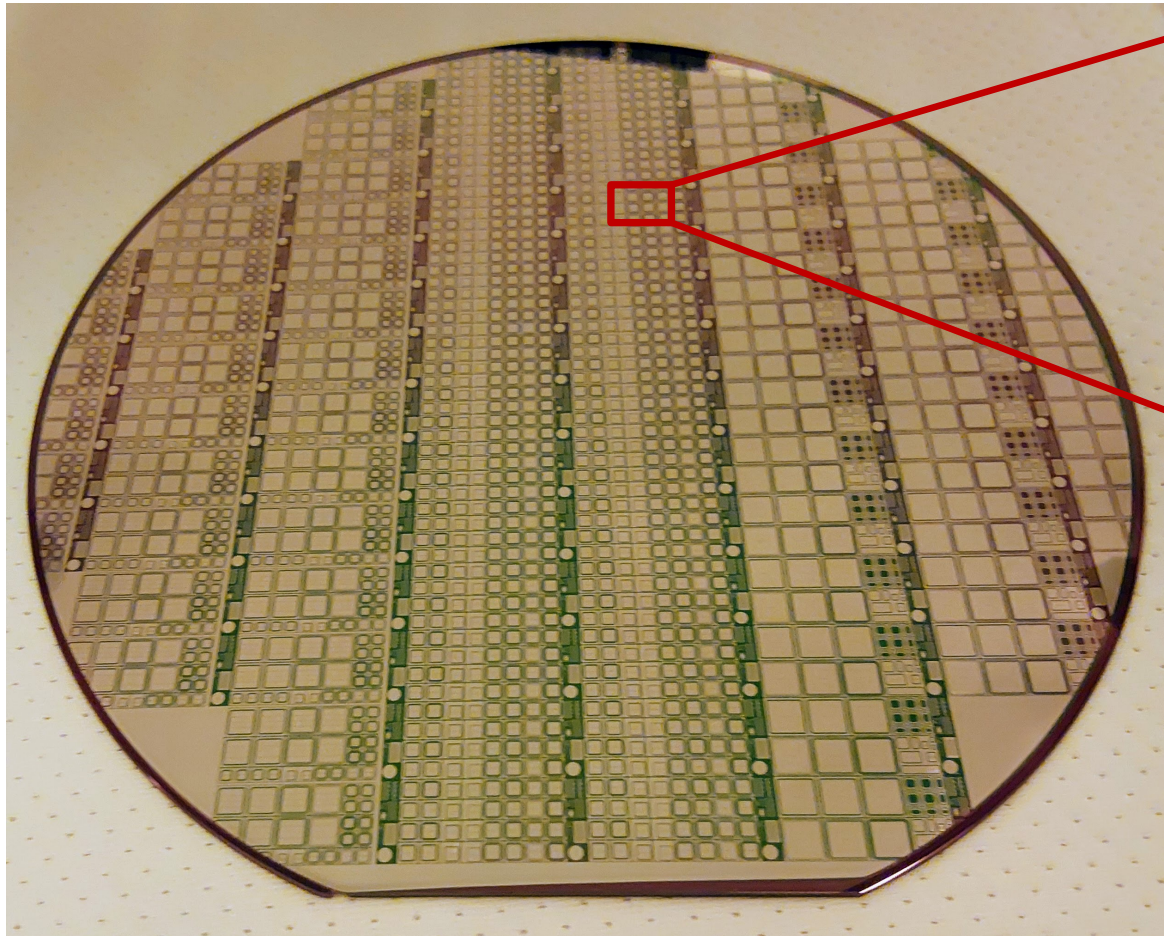
The EXFLU1 batch from FBK explores different innovation strategies to extend the radiation tolerance of silicon sensors up to the extreme fluences:

- ▷ carbon shield (in Backup)
- ▷ compensation
- ▷ new guard ring design
- ▷ thin substrates (15–45 μm)

→ **The EXFLU1 wafers exited the FBK clean room in November 2022**

The EXFLU1 Wafers

6" Wafer



⇒ The EXFLU1 testing has started



Compensated LGAD – Split Table

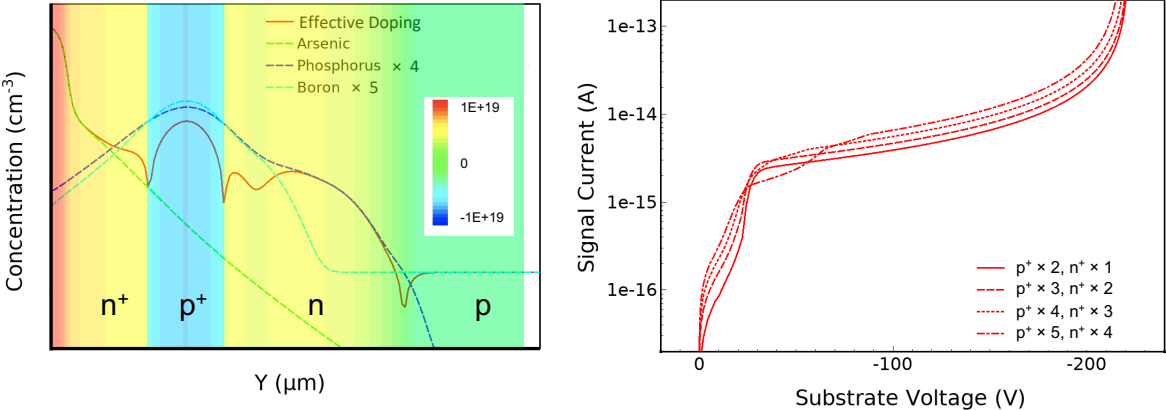
Wafer #	Thickness	p+ dose	n+ dose	C dose
6	30	2 a	1	
7	30	2 b	1	
8	30	2 b	1	
9	30	2 c	1	
10	30	3 a	2	
11	30	3 b	2	
12	30	3 b	2	
13	30	3 b	2	1.0
14	30	3 c	2	
15	30	5 a	4	

[a < b < c]

3 different combinations of p⁺ – n⁺ doping: 2 – 1, 3 – 2, 5 – 4

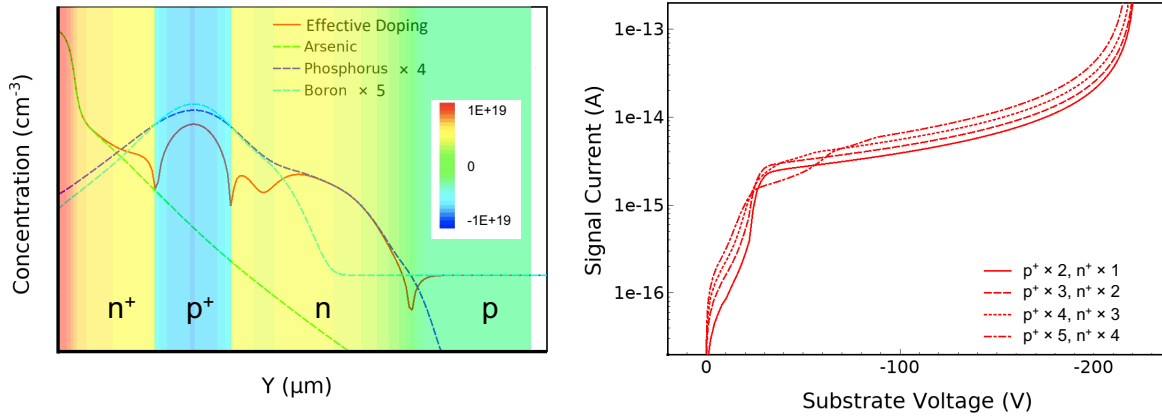
Compensated LGAD – I-V for different $p^+ - n^+$

Simulation

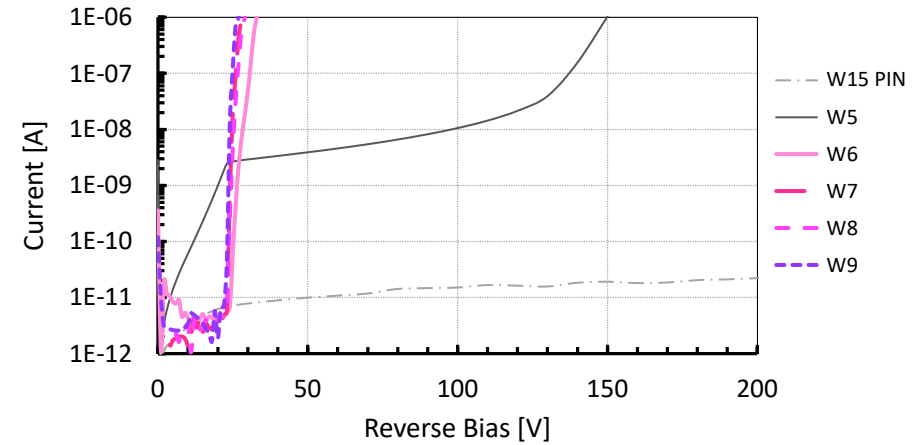


Compensated LGAD – I-V for different $p^+ - n^+$

Simulation



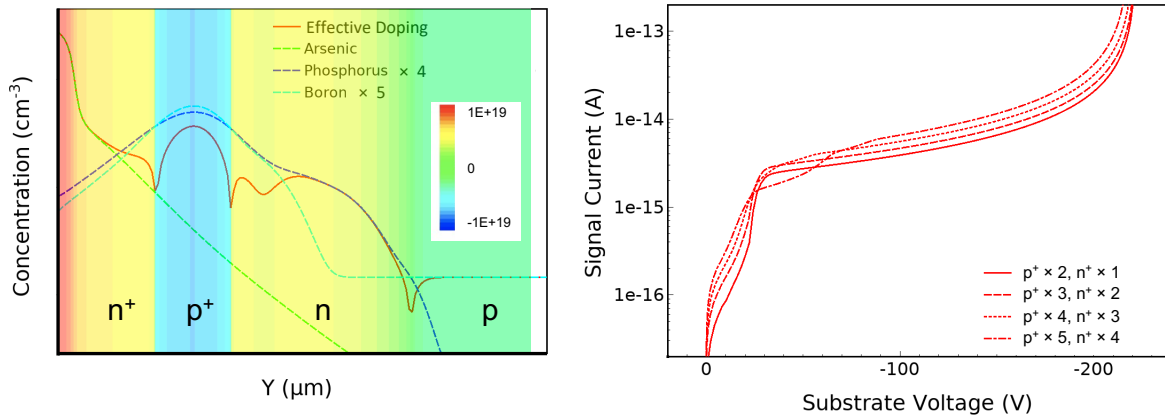
EXFLU1 – Compensated LGAD 2-1 – I-V



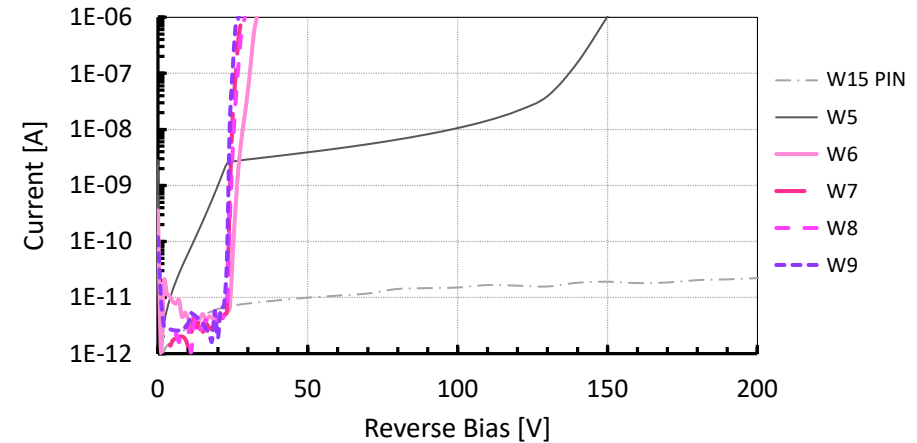
2-1

Compensated LGAD – I-V for different $p^+ - n^+$

Simulation

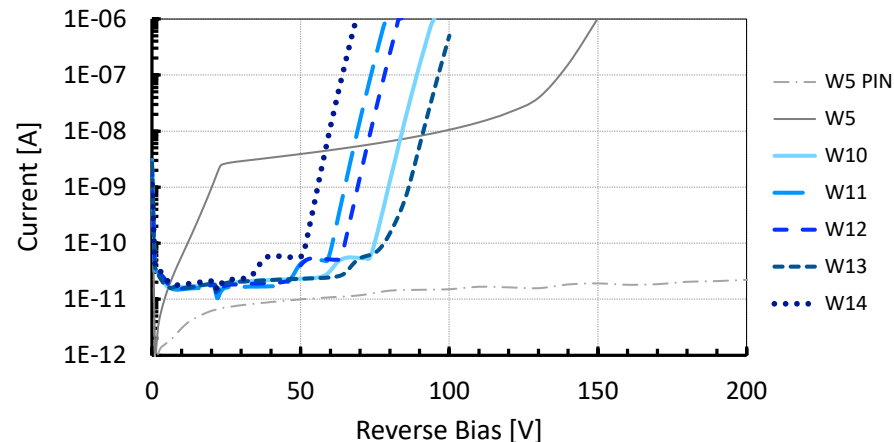


EXFLU1 – Compensated LGAD 2–1 – I-V



2 – 1

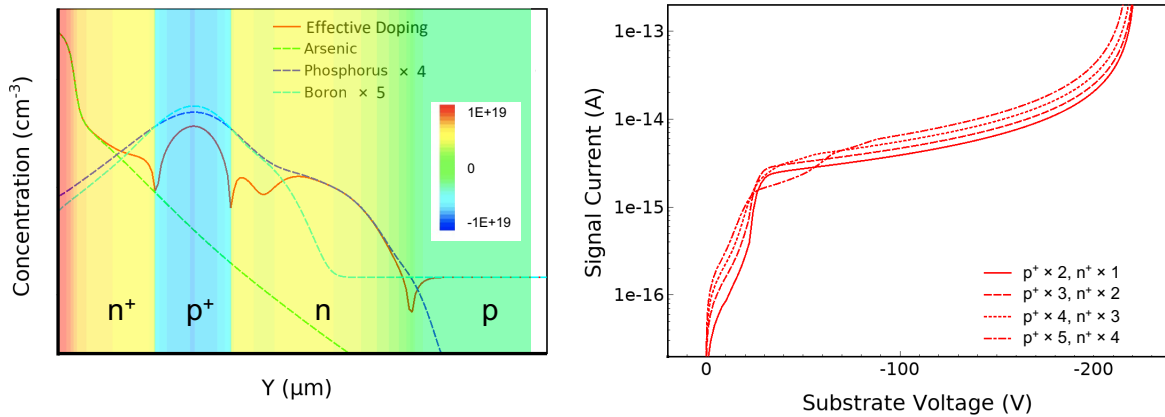
EXFLU1 – Compensated LGAD 3–2 – I-V



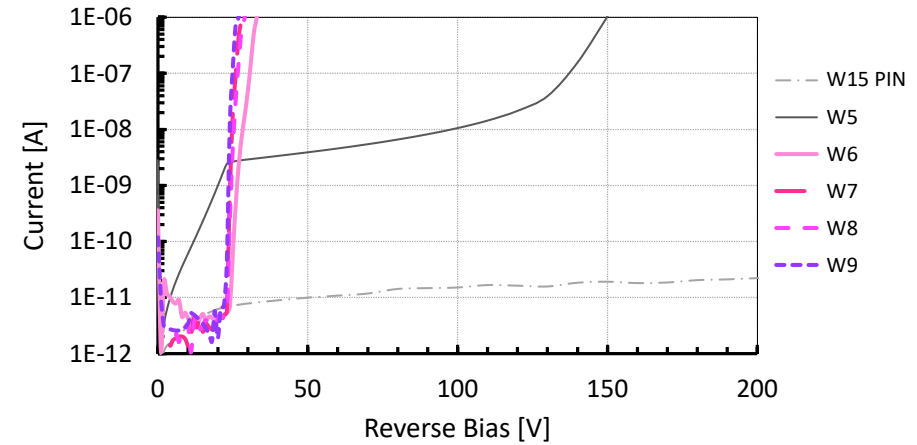
3 – 2

Compensated LGAD – I-V for different $p^+ - n^+$

Simulation

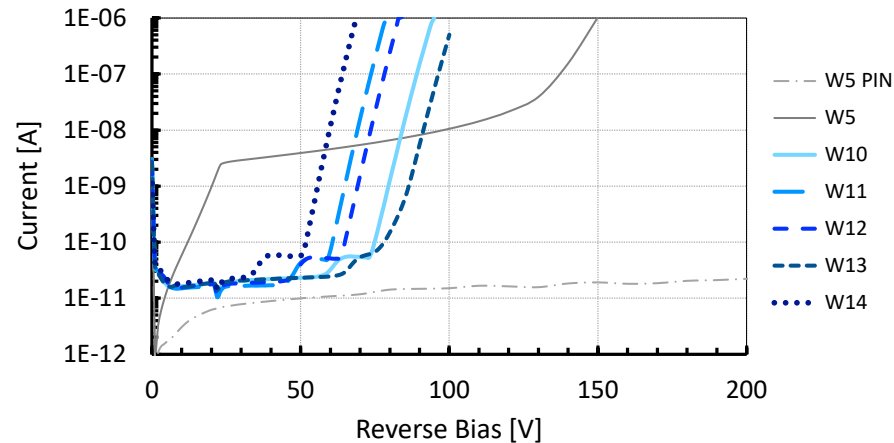


EXFLU1 – Compensated LGAD 2–1 – I-V



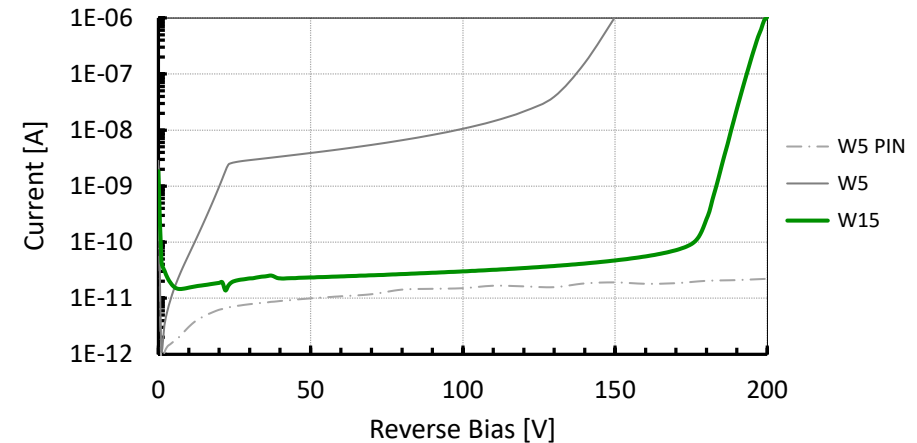
2-1

EXFLU1 – Compensated LGAD 3–2 – I-V



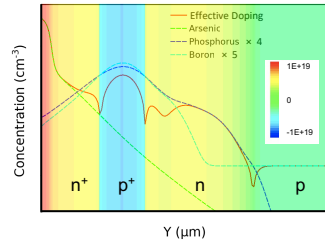
3-2

EXFLU1 – Compensated LGAD 5–4 – I-V



5-4

Compensated LGAD – Testing Campaign



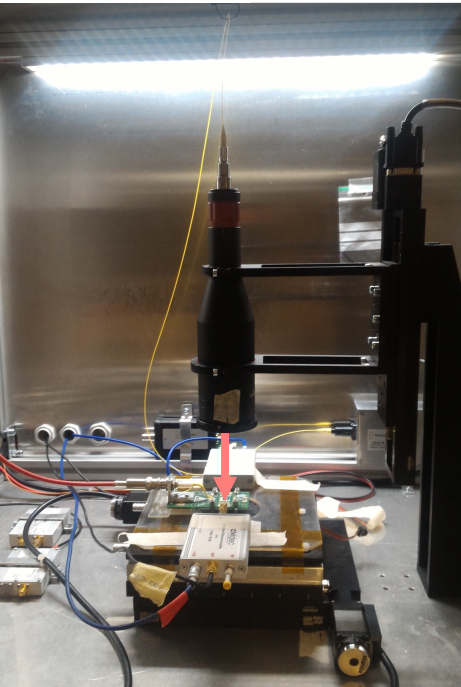
Observations from compensated LGAD sensors:

- ▶ the depletion of the gain layer region with bias reflects the depletion of different p-n junctions
- ▶ 2–1 sensors exhibit a too-high gain to be operated
- ▶ 3–2 sensors exhibit sharp gain performance compared to standard LGAD
- ▶ 5–4 sensors exhibit smaller gain with respect to standard LGAD
 - A correct tuning of the p⁺–n⁺ doping densities need to be extrapolated by the EXFLU1 sensors

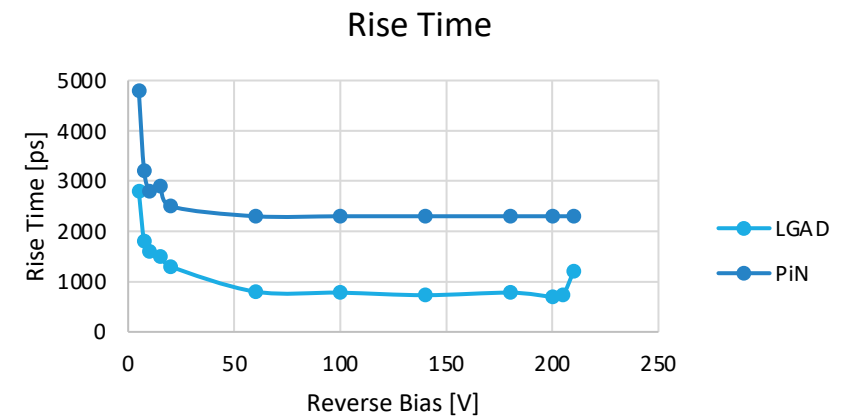
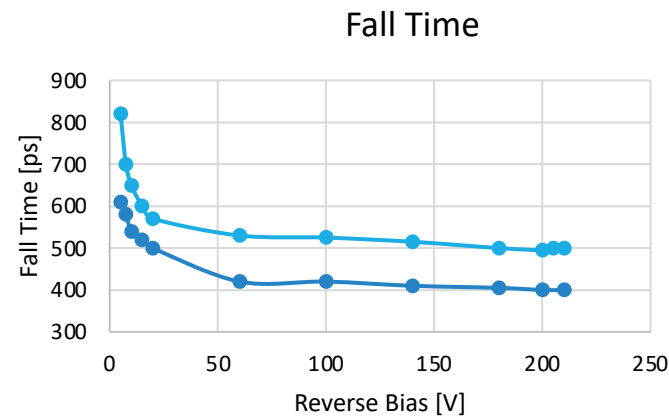
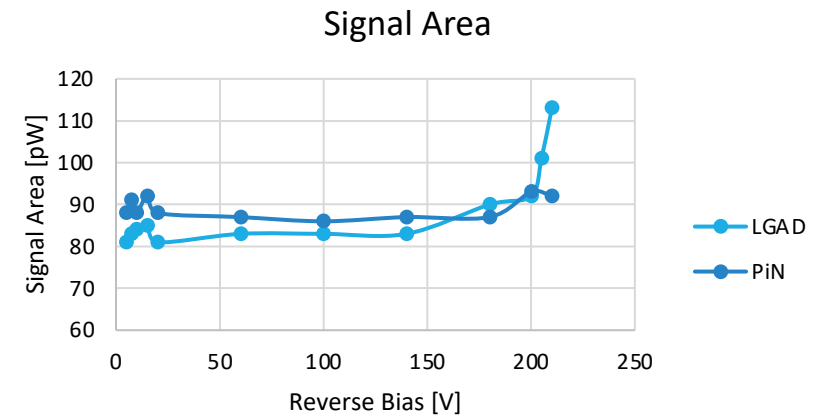
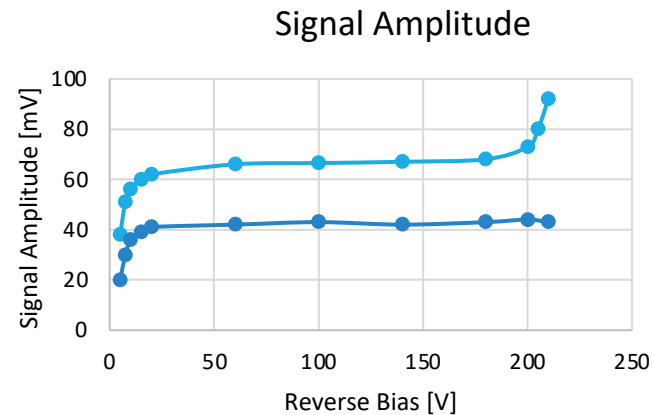
Investigation of the gain implant doping evolution:

- ▶ SIMS on the compensated LGAD are ongoing to precisely map the p⁺ and n⁺ implants
- ▶ The shape and doping density of the gain implant to be investigated before and after irradiation through I-V and C-V measurements
- ▶ The concurrent effect of acceptor and donor removals will be investigated
- ▶ TCT measurements with different laser wavelengths before and after irradiation will be used to study the signal shape evolution at different sensor depths

Compensated LGAD – Signals from TCT



Signal analysis from an LGAD and a PIN of W15 (5–4)



TCT Setup from Particulars

Pico-second IR laser at 1064 nm

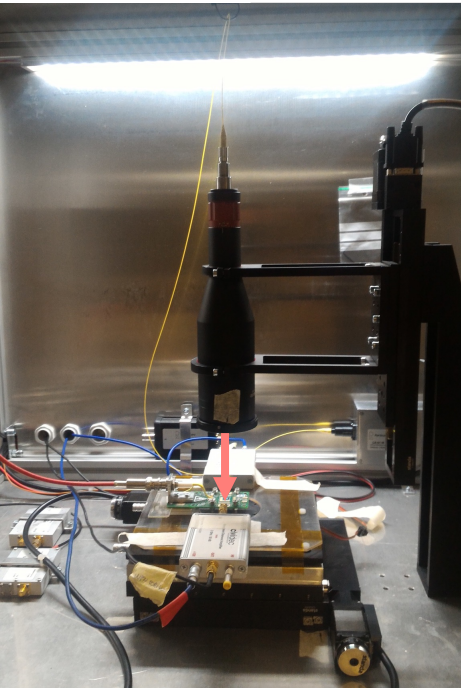
Laser spot diameter $\sim 10 \mu\text{m}$

Cividec Broadband Amplifier (40dB)

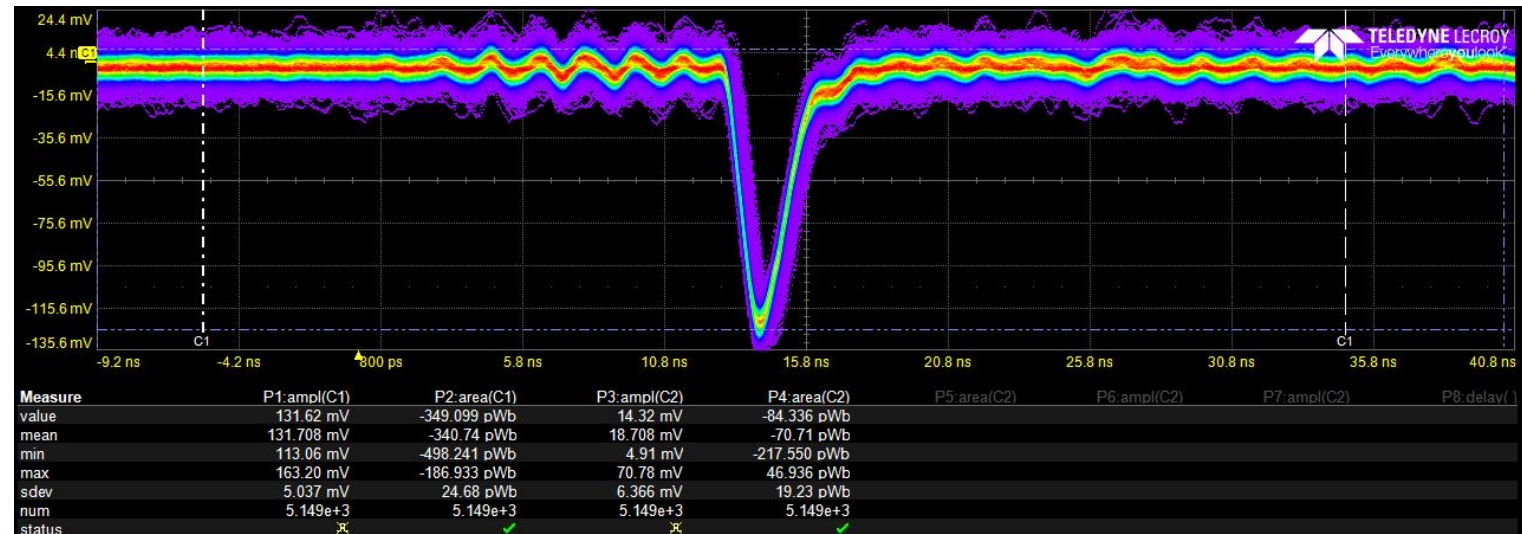
Oscilloscope LeCroy 640Zi

Room temperature

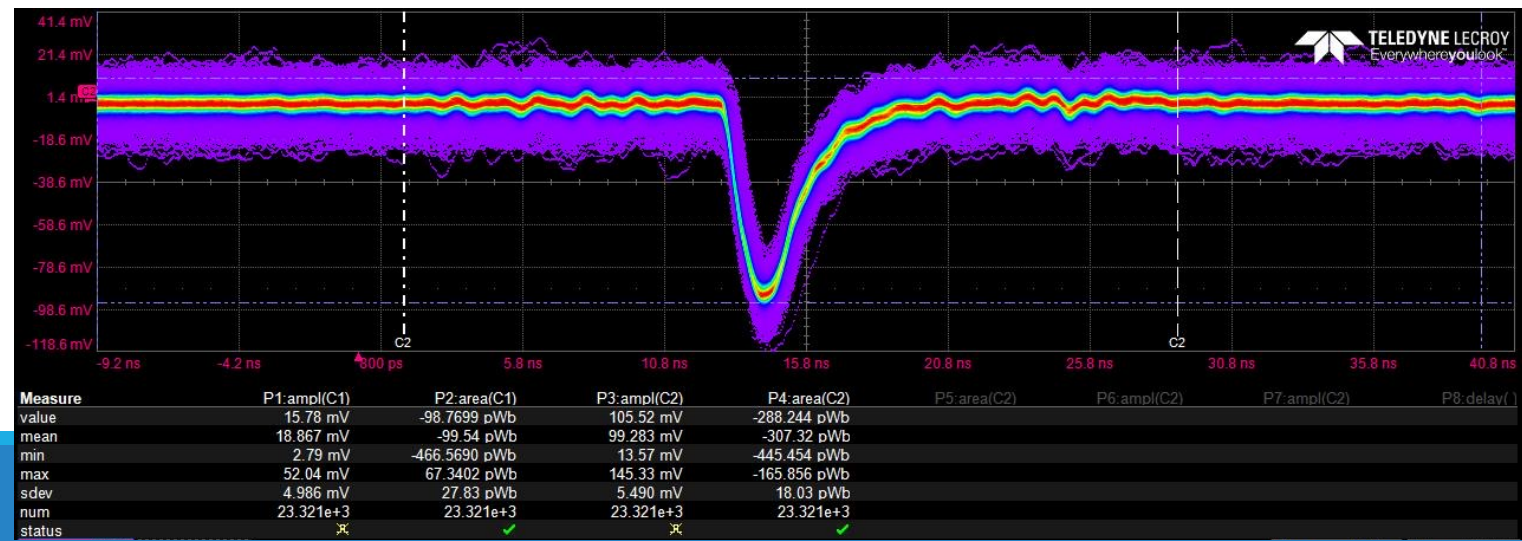
Compensated LGAD – Waveforms from TCT



Waveforms from an LGAD and a PIN of W15 (5–4) operated at $V_{bias} = 150\text{ V}$



W15
LGAD
 $V_{bias} = 150\text{ V}$

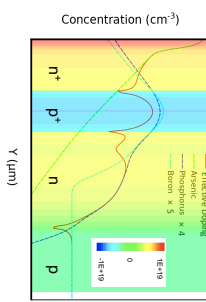


W15
PIN
 $V_{bias} = 150\text{ V}$

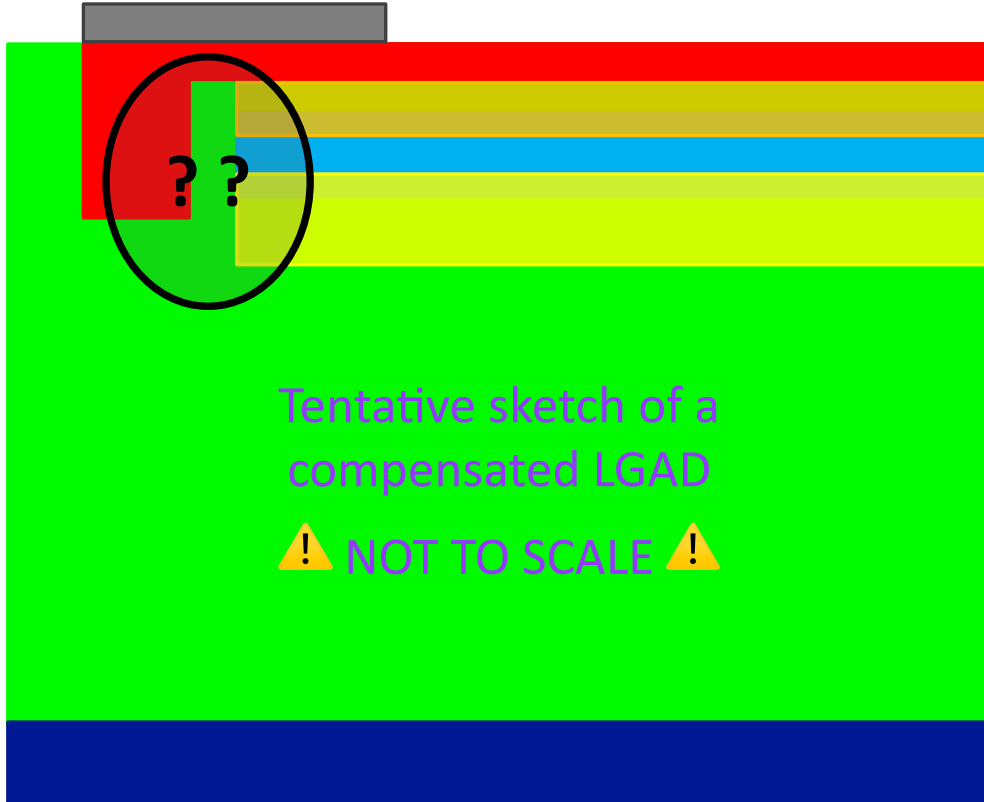
TCT Setup from Particulars

- Pico-second IR laser at 1064 nm
- Laser spot diameter $\sim 10\ \mu\text{m}$
- Cividec Broadband Amplifier (40dB)
- Oscilloscope LeCroy 640Zi
- Room temperature

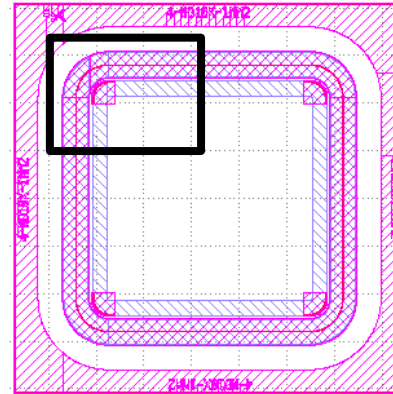
Compensated LGAD – 2D Scan with IR Laser



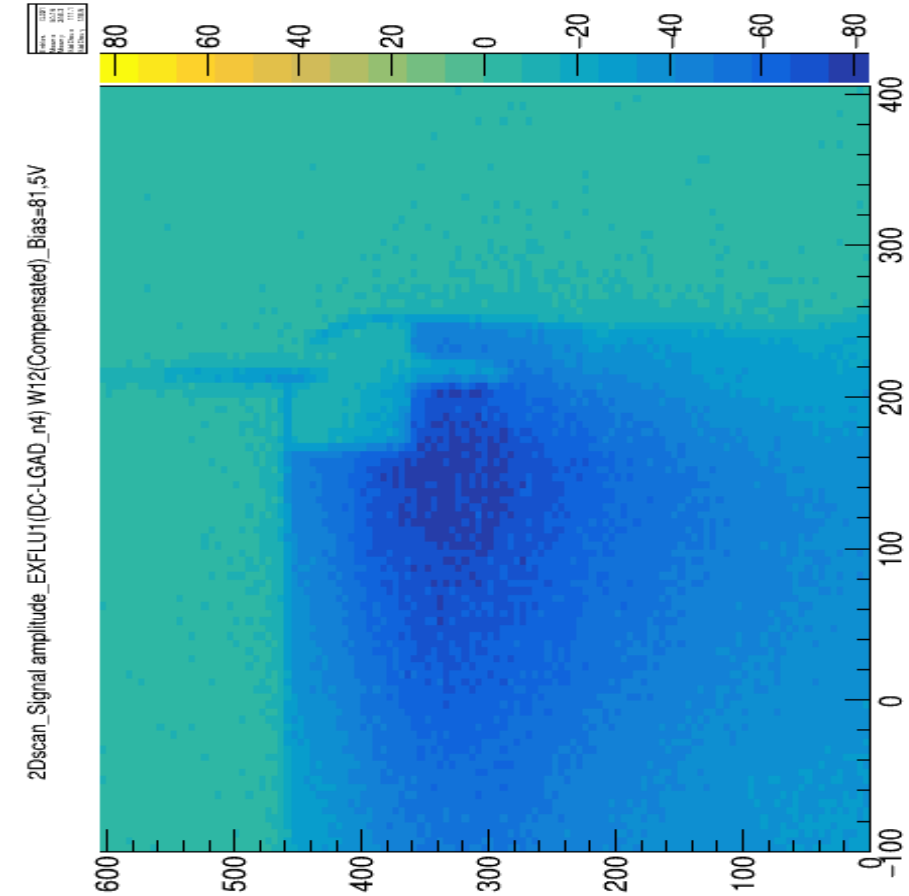
Ongoing characterisation: investigate with IR laser the edge of the compensated gain implants



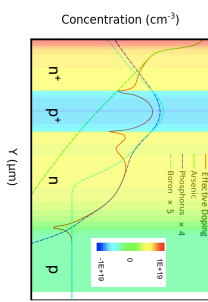
Scan surface



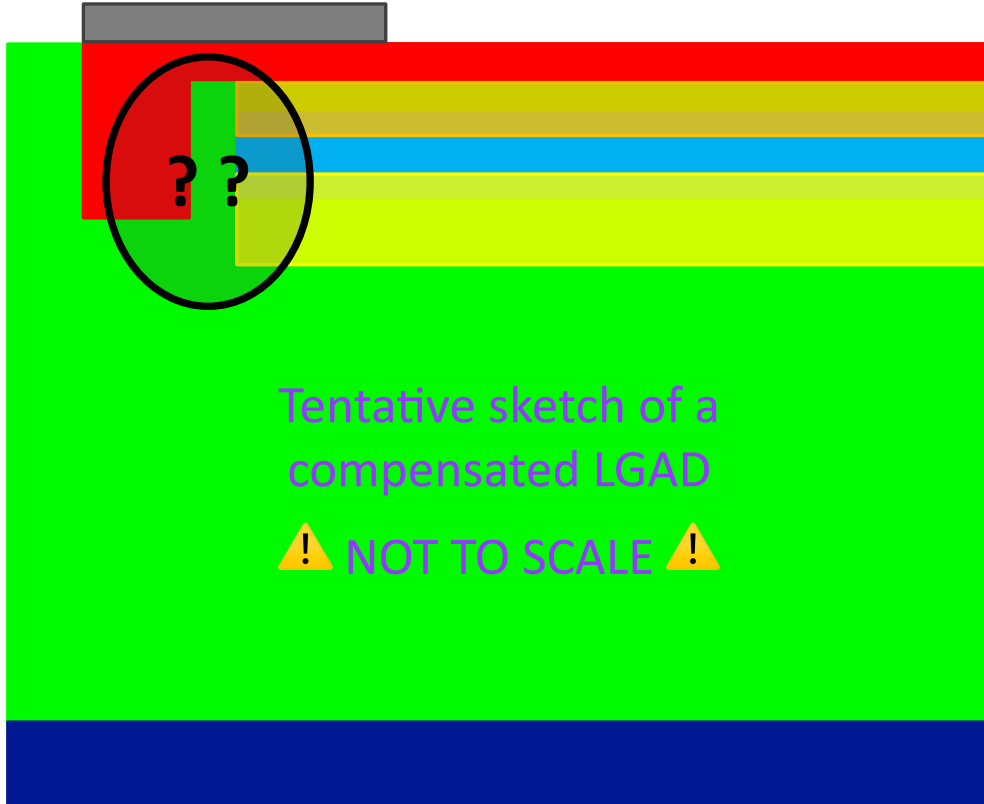
TCT scan with IR laser
Laser spot $\sim 10 \mu\text{m}$
Sensor from W12 (3–2)
 $V_{\text{bias}} = 81 \text{ V}$
Very close to BD



Compensated LGAD – 2D Scan with IR Laser



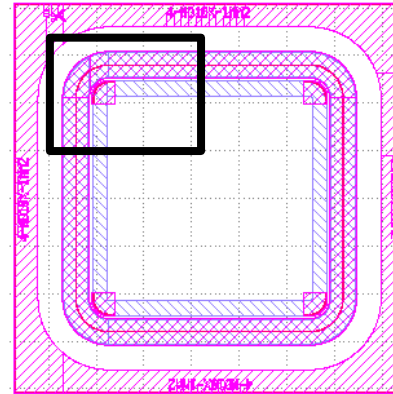
Ongoing characterisation: investigate with IR laser the edge of the compensated gain implants



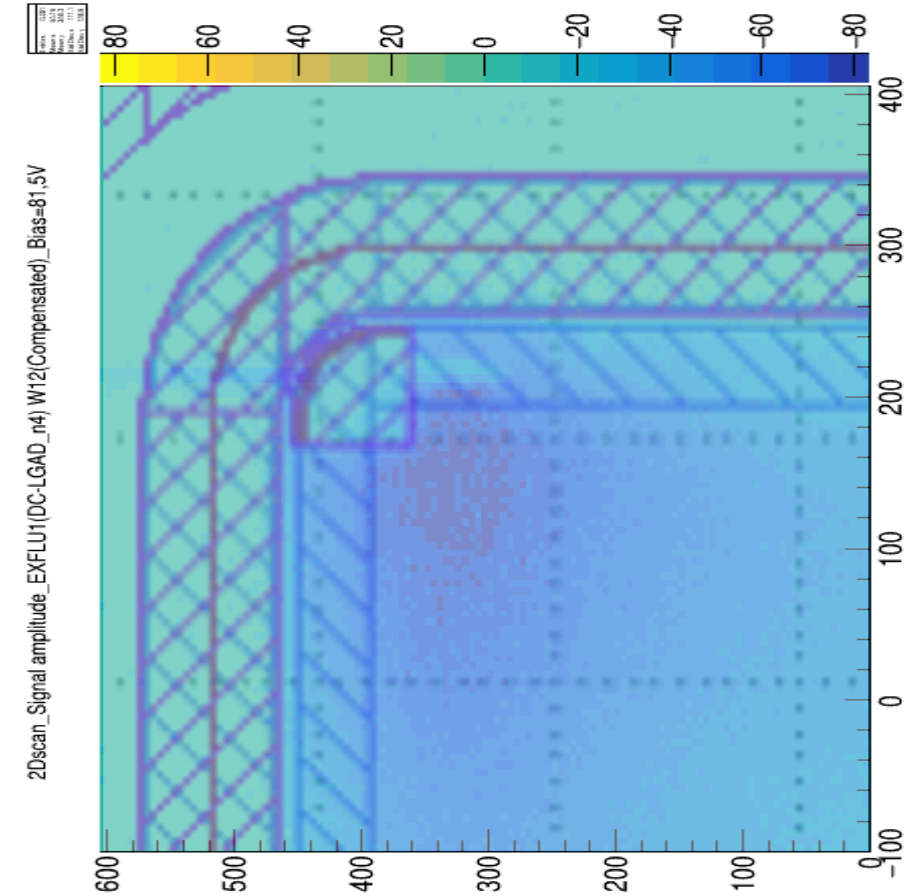
Tentative sketch of a compensated LGAD

! NOT TO SCALE !

Scan surface



TCT scan with IR laser
Laser spot $\sim 10 \mu\text{m}$
Sensor from W12 (3–2)
 $V_{\text{bias}} = 81 \text{ V}$
Very close to BD



→ No issues observed at the edge of the compensated gain implants

Compensated LGAD produced by HPK

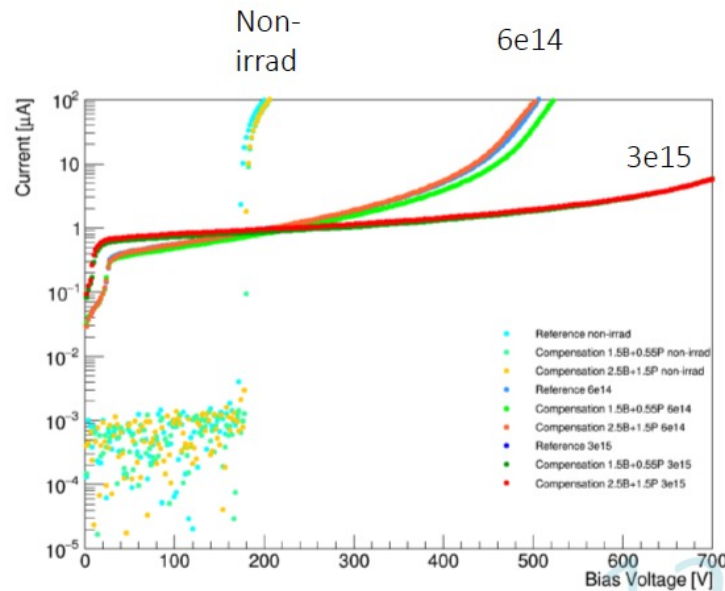
Presented by K. Hara at TREDI2023 [[link](#)]

Radiation tolerance improvement – trial2

Compensation

Result not promising...
 Not much change by two different compensation parameters
 Initial compensation works perfect

What does this mean?



How should we understand the results?

$$N_A(\phi) - N_D(\phi) = N_A(0) \cdot e^{-C_A\phi} - N_D(0) \cdot e^{-C_D\phi}$$

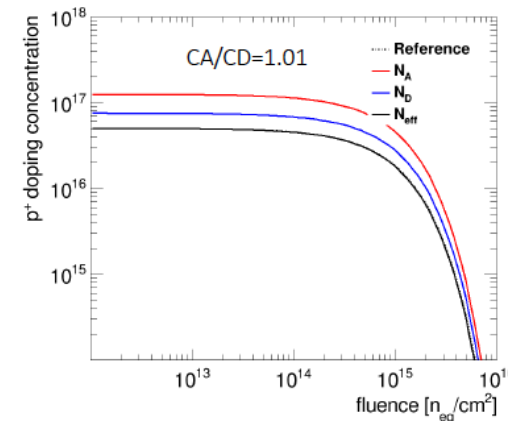
If $C_A = C_D$

$$N_A(\phi) - N_D(\phi) = (N_A(0) - N_D(0)) \cdot e^{-C_A\phi}$$

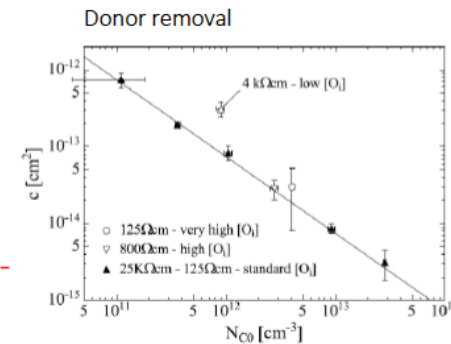
reference

$$N_A(\phi) = N_A(0) \cdot e^{-C_A\phi}$$

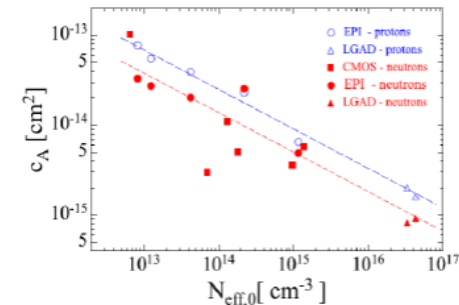
Reduction of effective p+ must be the same as non-compensated case



Previous data



Acceptor removal



13

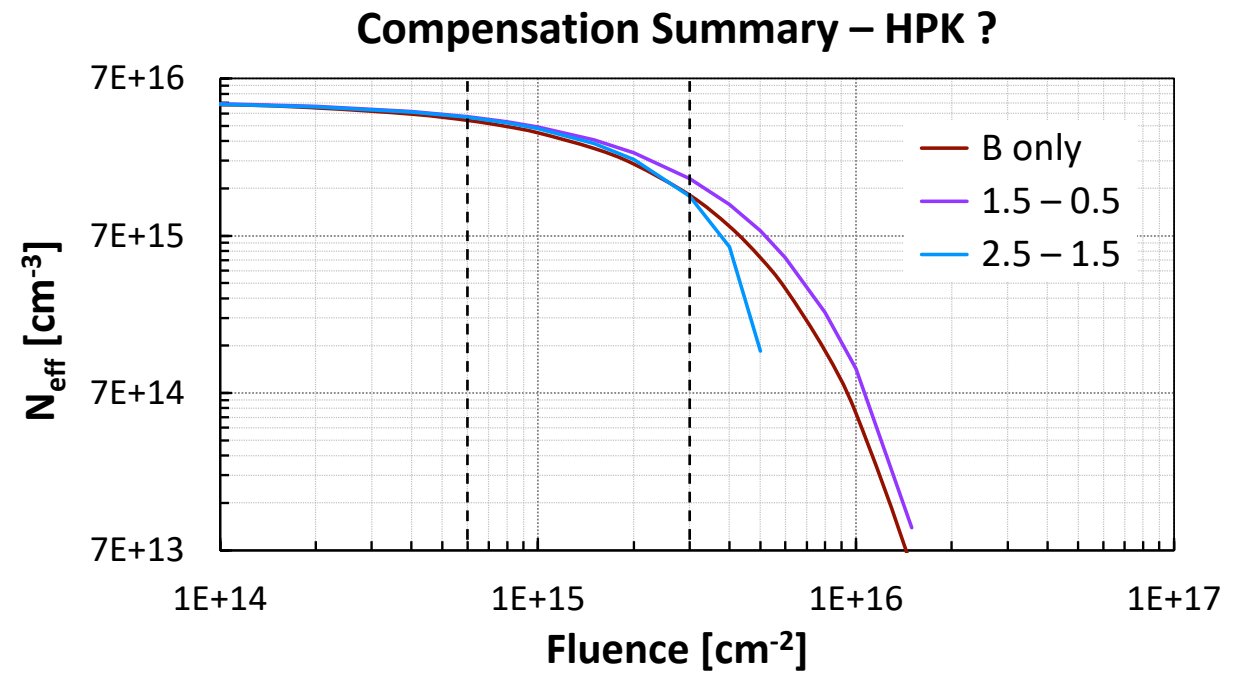
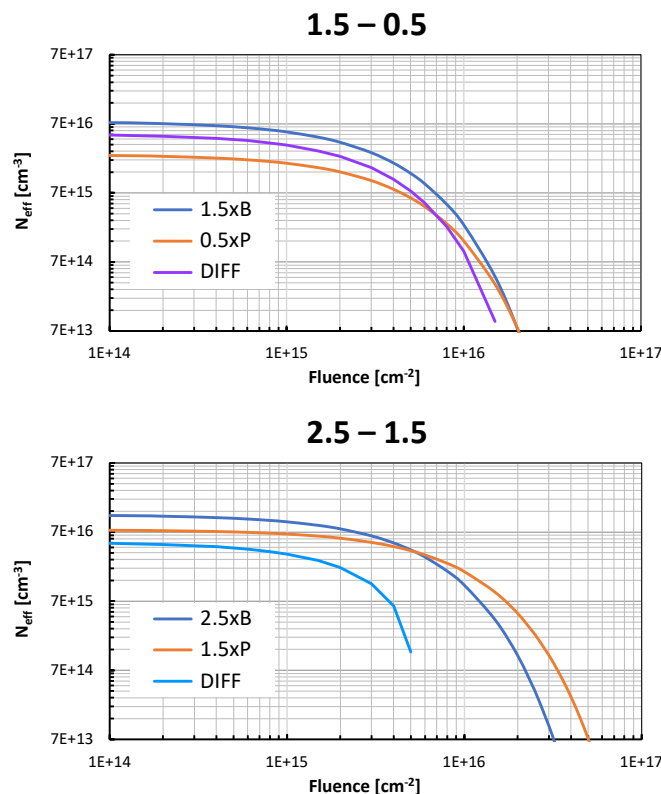
Compensated LGAD from HPK – c_A vs c_D ?

What can we learn from HPK compensated LGAD?

c_A and (presumably) c_D depends on the effective acceptor and donor densities

At fluences of $6E14$ & $3E15$ $n_{eq}/cm^2 \rightarrow p^+ - n^+$ compensated doping is the same as before irradiation

$\Rightarrow c_A > c_D$?



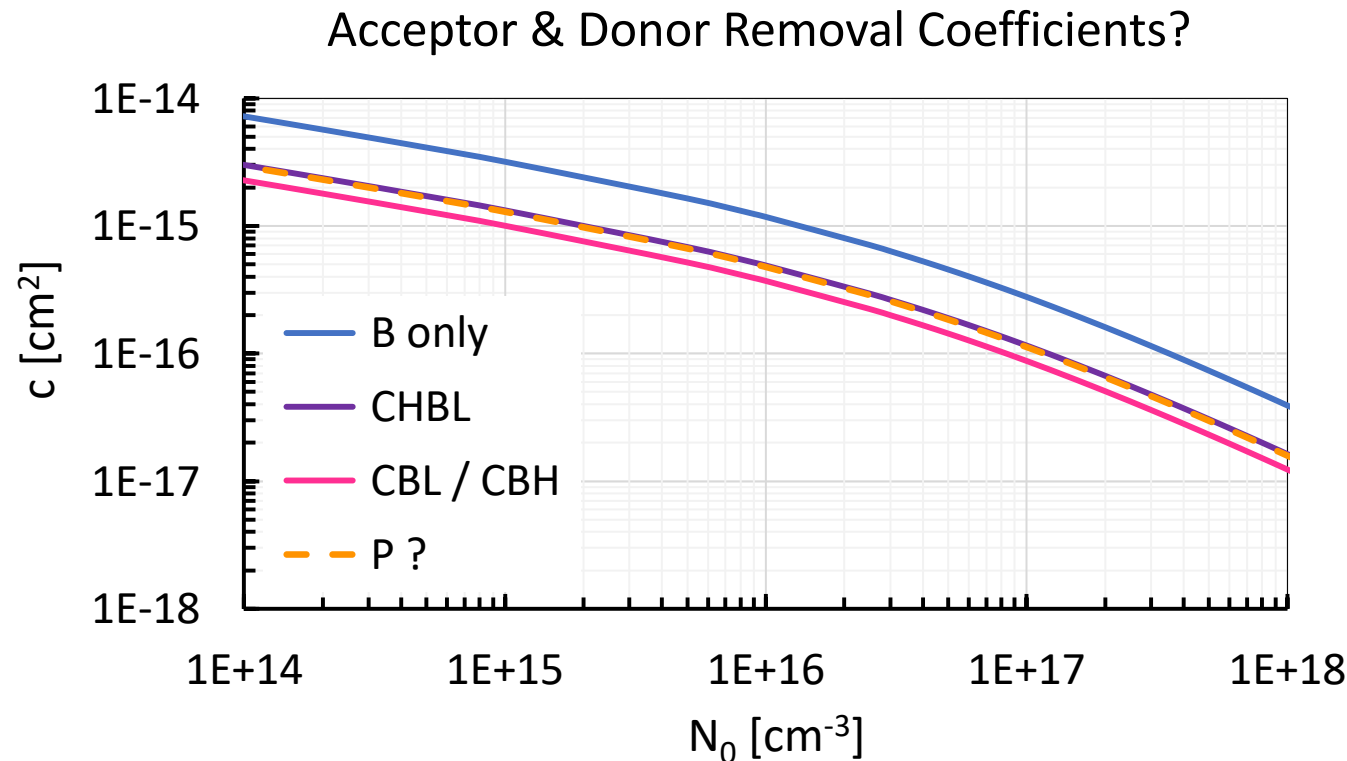
Compensated LGAD from HPK – c_A vs c_D ?

What can we learn from HPK compensated LGAD?

c_A and (presumably) c_D depends on the effective acceptor and donor densities

At fluences of $6E14$ & $3E15$ $n_{eq}/cm^2 \rightarrow p^+ - n^+$ compensated doping is the same as before irradiation

$\Rightarrow c_A > c_D$?



$c_A / c_D = 2.47$
to reproduce
the HPK results

p-in-n LGAD Production

A production batch is needed to study the donor removal coefficient, c_D

Donor removal has been studied for doping densities of $10^{12} - 10^{14}$ atoms/cm³

We need to study donor removal in a range $10^{16} - 10^{18}$ atoms/cm³

NB: Oxygen has for donor removal a very similar effect of Carbon to acceptor removal



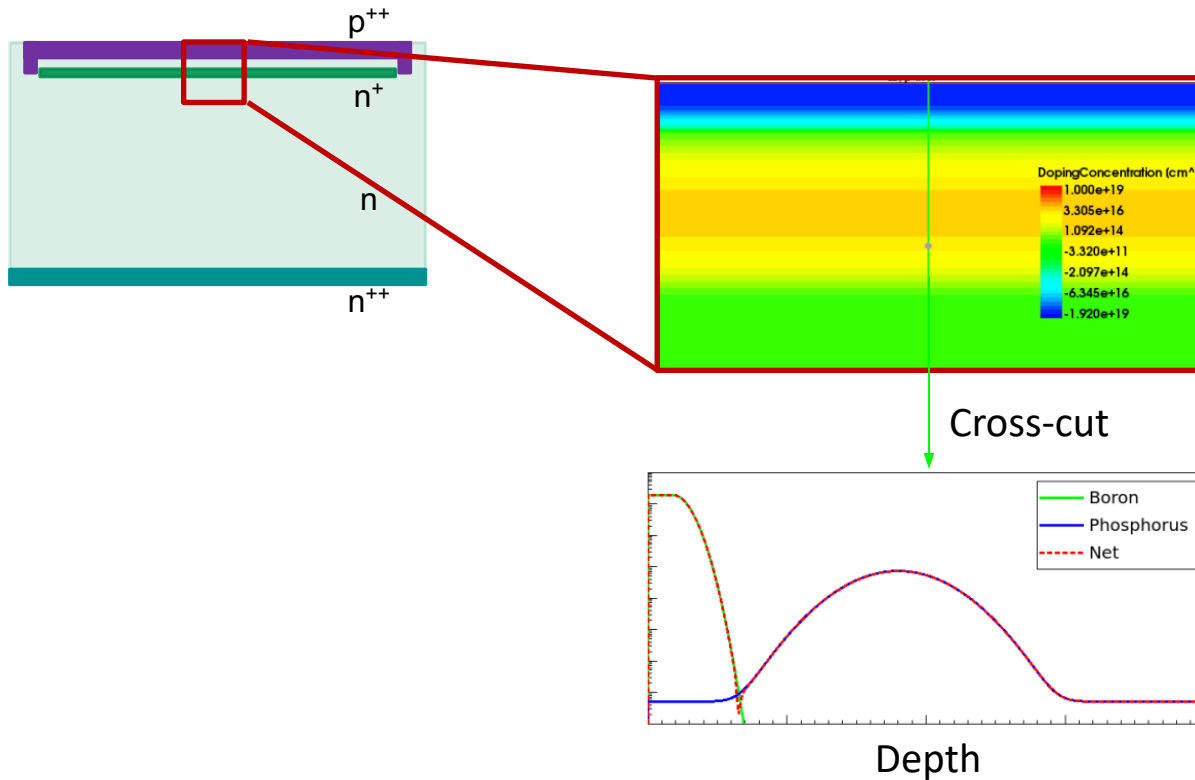
p-in-n LGAD

→ **The main goal of the p-in-n LGAD production is to study the c_D evolution and its interplay with Oxygen co-implantation**

First p-in-n LGAD (NLGAD) batch produced by CNM [[link](#)]

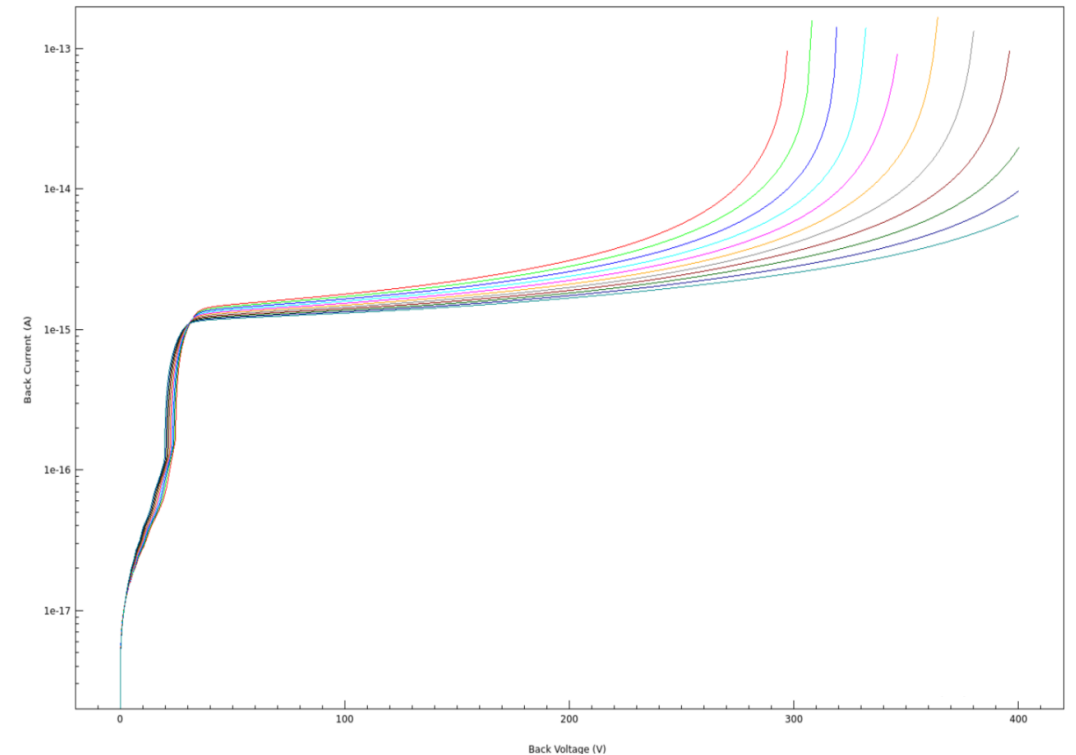
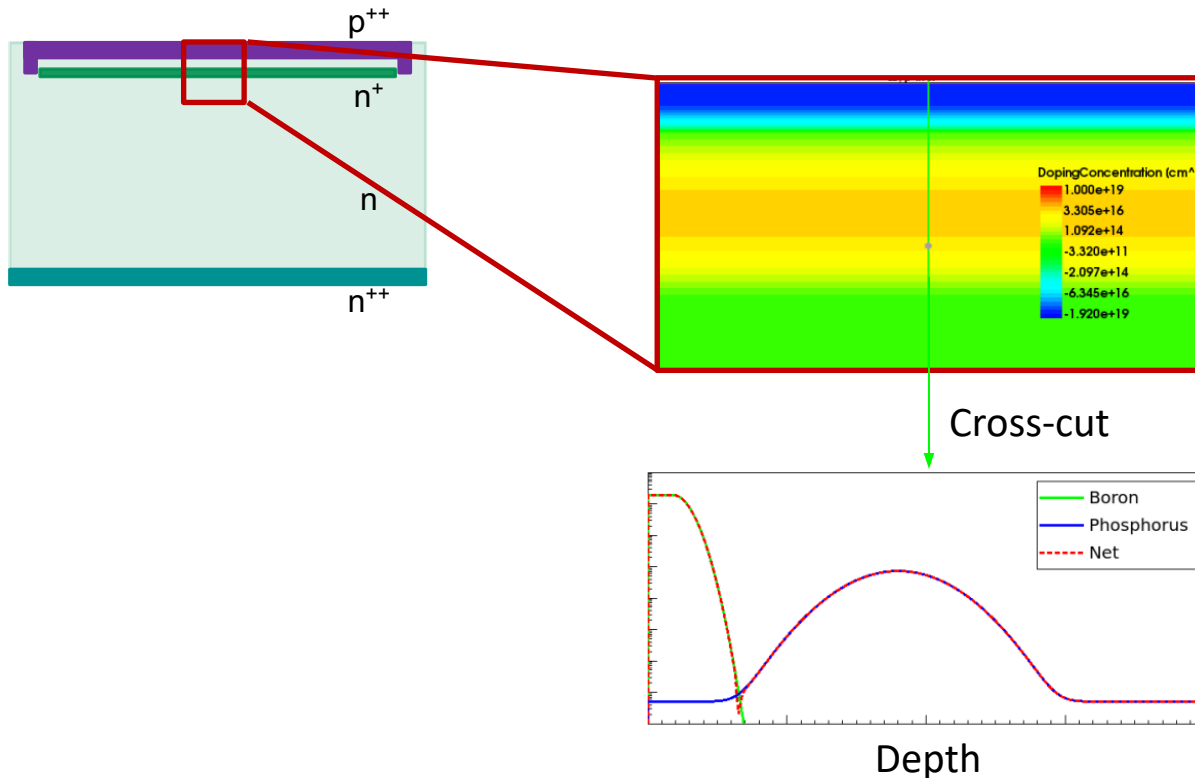
p-in-n LGAD – Simulation & Design

Process simulation is used to design the p⁺⁺ electrode with Boron (TCAD Silvaco)



p-in-n LGAD – Simulation & Design

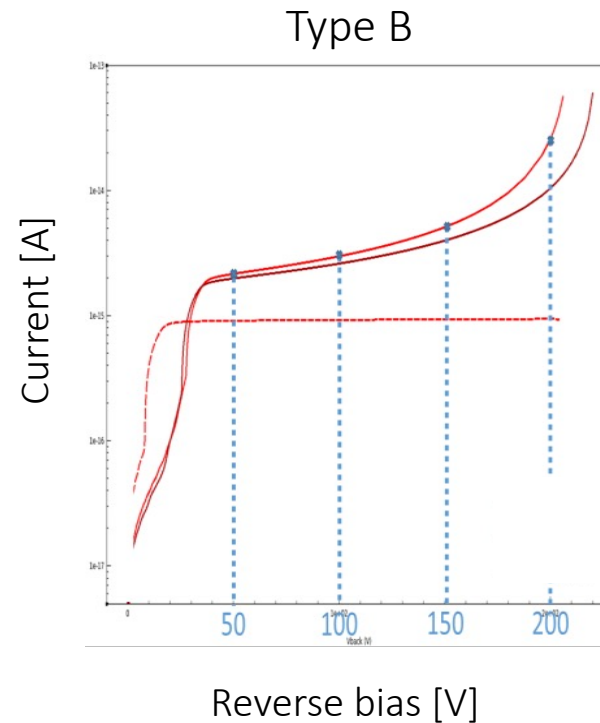
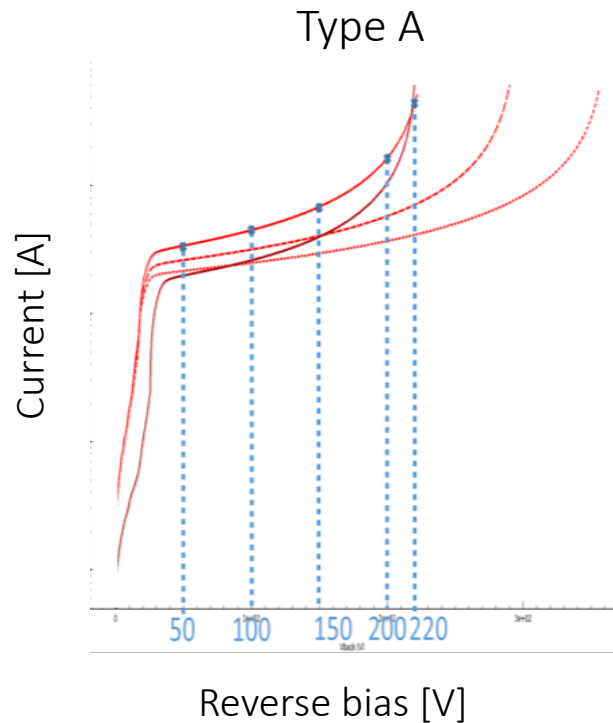
Process simulation is used to design the p⁺⁺ electrode with Boron (TCAD Silvaco)



→ The simulation of the electrostatic behaviour shows good performances of the I-V characteristics for different p⁺⁺ designs (TCAD Synopsys)

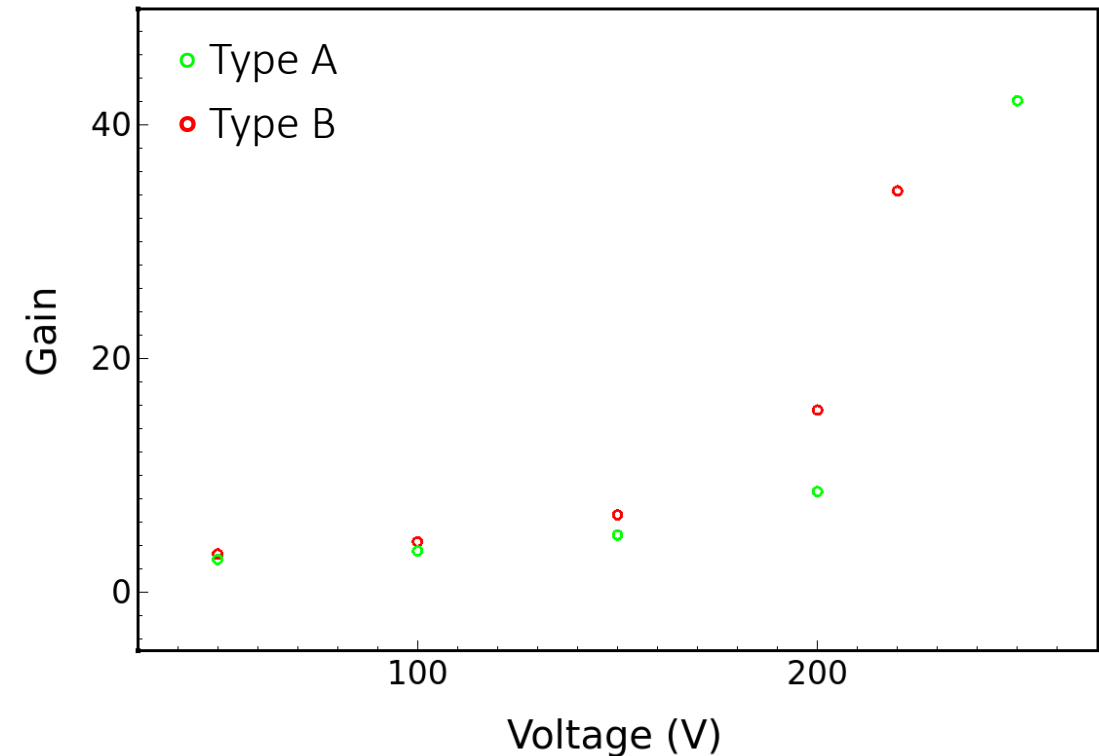
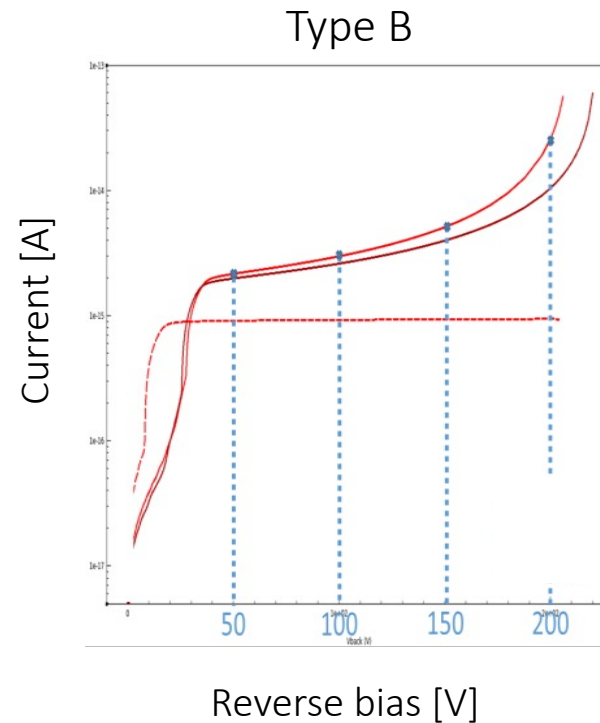
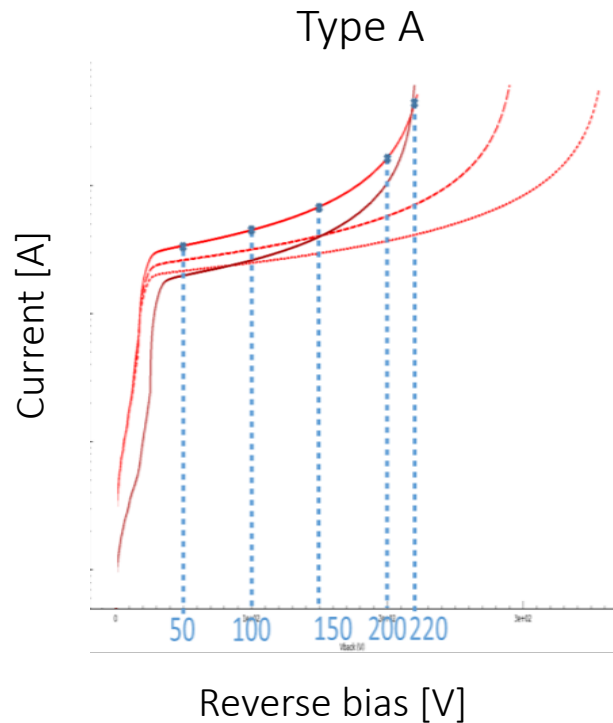
p-in-n LGAD – Simulation & Design

Different designs of the n^+ gain layer are investigated



p-in-n LGAD – Simulation & Design

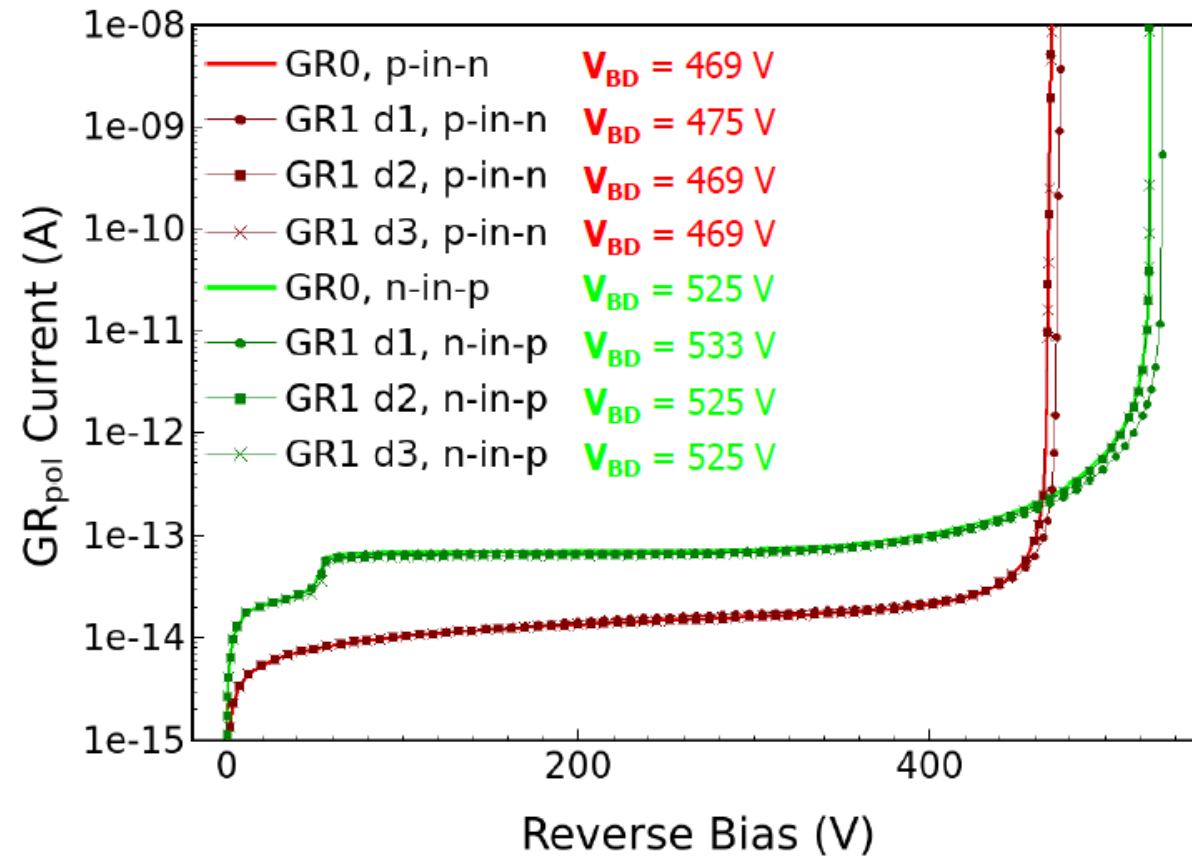
Different designs of the n⁺ gain layer are investigated



→ Both electrical and transient characteristics exhibit good operation of the sensors

p-in-n LGAD – Simulation & Design

Different designs of the guard ring structures are investigated



Participation to an RD50 Project

Defect engineering in PAD diodes mimicking the gain layer in LGADs

PI: Ioana Pintilie (Bucharest, Nat. Inst. Mat. Sci.)

Participants: Michael Moll (CERN), Kevin Lauer (CiS), Gregor Kramberger (JSI),
Eckhart Fretwurst (Hamburg University), Valentina Sola (INFN-Torino),
and Tomas Ceponis (Vilnius University)

‘The proposed project is focusing on the acceptor removal process (ARP) in the irradiated gain layer of LGAD sensors, aiming to understand it and parametrize it for various content of B, C and O impurities and irradiation fluences, in order to find proper defect engineering solutions to maximize the radiation hardness of the gain layers.’

⇒ To study and characterise acceptor and donor removal mechanisms

Project Budget

The project has been funded with 140k EUR + 25%

Matching funds of 140k EUR is being provided by the Participant Institutions

INFN funding

- 60k EUR for personnel, to cover 24 months of experienced Post-Docs
 - 1 Post-Doc hired, 1 Post-Doc selection in progress
- 30k EUR of consumables, to cover the cost of dopant implantation at external services
 - in progress

FBK funding

- 50k EUR for the 2 sensor production batches
 - 1 batch completed, 1 batch pending

References

Publications:

- [1] V. Sola et al., A compensated design of the LGAD gain layer, Nucl. Inst. Meth. A 1040 (2022) 167232, [doi:10.1016/j.nima.2022.167232](https://doi.org/10.1016/j.nima.2022.167232)
- [2] T. Croci et al., Development and test of innovative Low-Gain Avalanche Diodes for particle tracking in 4 dimensions, Nucl. Inst. Meth. A 1047 (2023) 167815, [doi.org:10.1016/j.nima.2022.167815](https://doi.org/10.1016/j.nima.2022.167815)
- [3] T. Croci et al., TCAD optimization of LGAD sensors for extremely high fluence applications, J. Instrum. 18 (2023) C01008, [doi:10.1088/1748-0221/18/01/C01008](https://doi.org/10.1088/1748-0221/18/01/C01008)

Presentations:

- [1] T. Croci et al., Development and test of innovative Low-Gain Avalanche Diodes for particle tracking in 4 dimensions, 15th Pisa Meeting on Advanced Detectors (2022) La Biodola, Italy – poster
- [2] T. Croci et al., TCAD optimization of LGAD sensors for extremely high fluence applications, 23rd International Workshop on Radiation Imaging Detectors - IWORID (2022) Riva del Garda, Italy – poster
- [3] F. Moscatelli et al., TCAD simulations of innovative Low-Gain Avalanche Diodes for particle detector design and optimization, The 31st International Workshop on Vertex Detectors (2022) Tateyama Resort Hotel, Japan – invited talk
- [4] V. Sola et al., Innovations in the design of thin silicon sensors for extreme fluences, IEEE Nuclear Science Symposium (2022) Milano (Italy) – parallel talk
- [5] V. Sola et al., Innovations in the design of thin silicon sensors for extreme fluences, 41st RD50 Workshop (2022) Sevilla (Spain) – plenary talk
- [6] V. Sola et al., Advances in LGAD Technology for High Radiation Environments, 18th Trento Workshop on Advanced Silicon Radiation Detectors (2023) Trento (Italy) – plenary talk

Summary on the eXFlu-innova Activities

The eXFlu-innova activities are ongoing

- ▷ The p^+n^+ design has been completed – Deliverable 1
- ▷ The p^+n^+ production batch has been completed – Part of Deliverable 2
- ▷ The characterisation and testing on the p^+n^+ sensors have started
- ▷ The design of the p-in-n LGAD production is ongoing

⇒ Activities of the eXFlu-innova projects are proceeding timely



This project has received funding from the European Union's Horizon 2020 Research and Innovation programme under Grant Agreement No 101004761



*Thank
You*

Backup

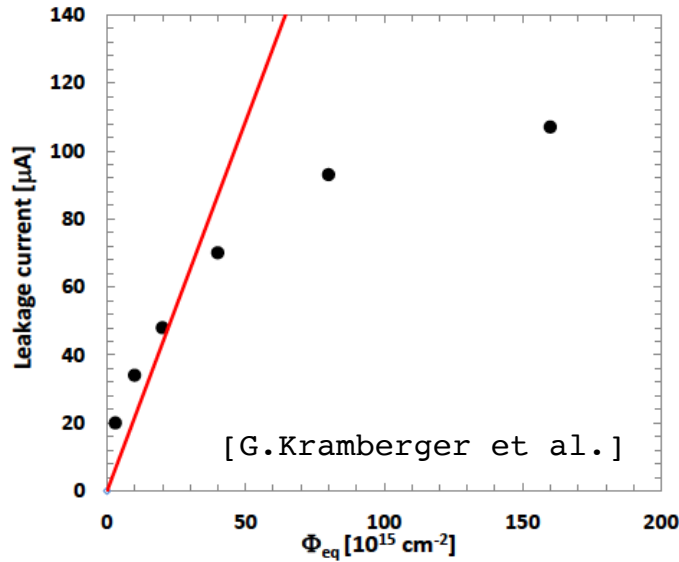
The Goals

- Measure the properties of silicon sensors at fluences above 10^{16} cm^{-2}
- Design planar silicon sensors able to work in the fluence range $10^{16} - 10^{17} \text{ cm}^{-2}$
- Estimate if such sensors generate enough charge to be used in a detector exposed to extreme fluences

⇒ The R&D activity has started

Saturation

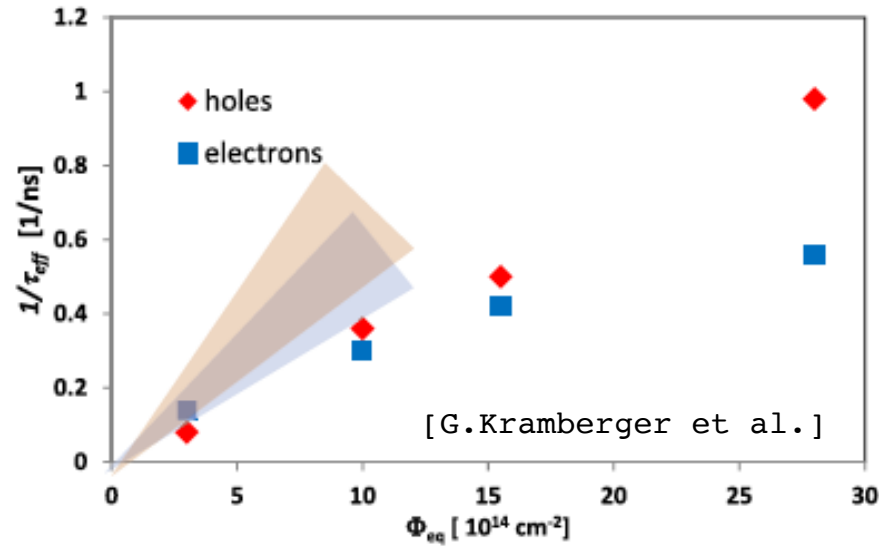
At fluences above $5 \cdot 10^{15} \text{ cm}^{-2}$ → **Saturation of radiation effects observed**



Leakage current saturation

$$I = \alpha V \Phi$$

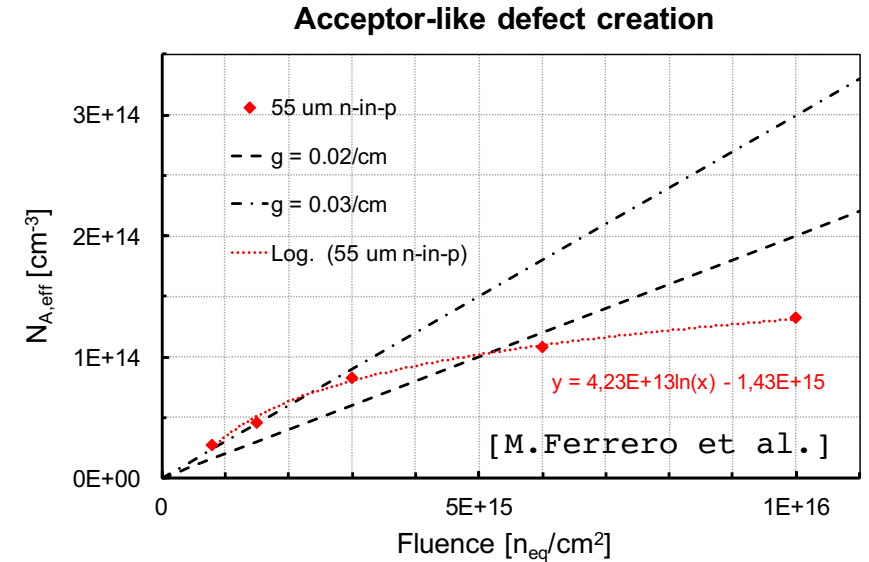
α from linear to logarithmic



Trapping probability saturation

$$1/\tau_{\text{eff}} = \beta \Phi$$

β from linear to logarithmic



Acceptor creation saturation

$$N_{A,\text{eff}} = g_c \Phi$$

g_c from linear to logarithmic

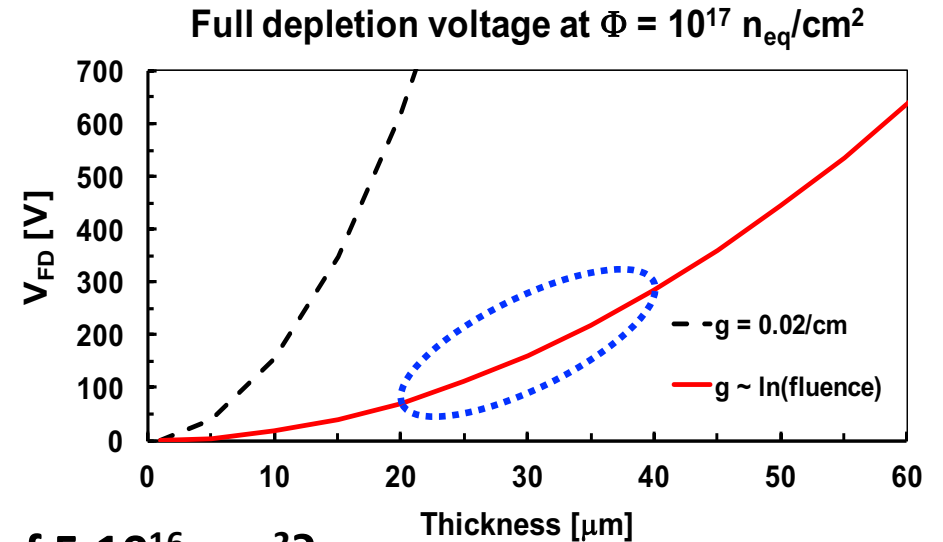
Silicon detectors irradiated at fluences $10^{16} - 10^{17} \text{ cm}^{-2}$ do not behave as expected → **They behave better**

Thin Substrates

$$V_{FD} = e |N_{eff}| d^2 / 2\epsilon$$

Saturation **Reduce thickness**

At high fluences, only thin substrates can be fully depleted



What does it happen to a **25 μm sensor** after a fluence of $5 \cdot 10^{16} \text{ cm}^{-2}$?

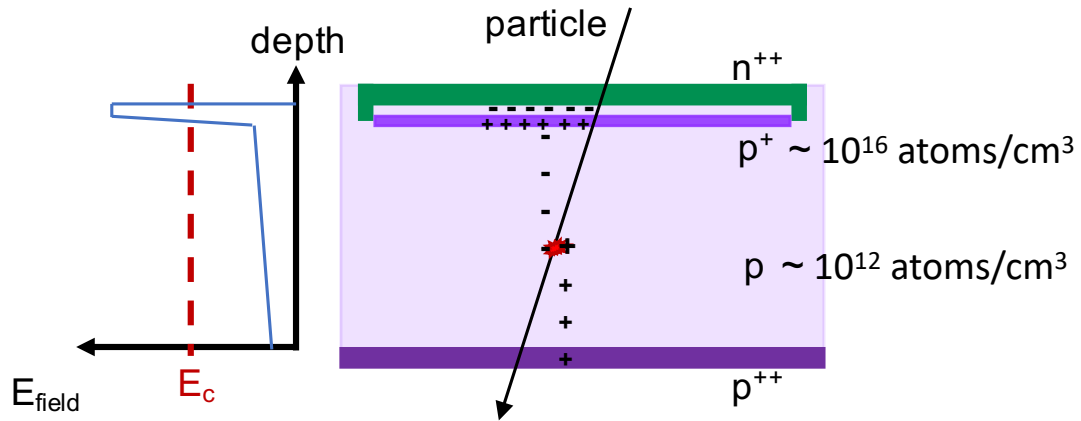
- ▶ It can still be depleted
- ▶ Trapping is limited (small drift length)
- ▶ Dark current is low (small volume)

However: charge deposited by a MIP ~ 0.25 fC

- This charge is lower than the minimum charge requested by the electronics (~ 1 fC for tracking, $\gtrsim 5$ fC for timing)
- **Need a gain of at least ~ 5** in order to efficiently record a hit

**Optimal candidate:
LGAD sensors**

Low-Gain Avalanche Diodes – LGADs



Minimum charge requested by the electronics

→ **~ 1 fC** for tracking

→ **$\gtrsim 5$ fC** for timing

Charge from a MIP crossing thin sensors

→ **~ 0.1 fC every 10 μm**

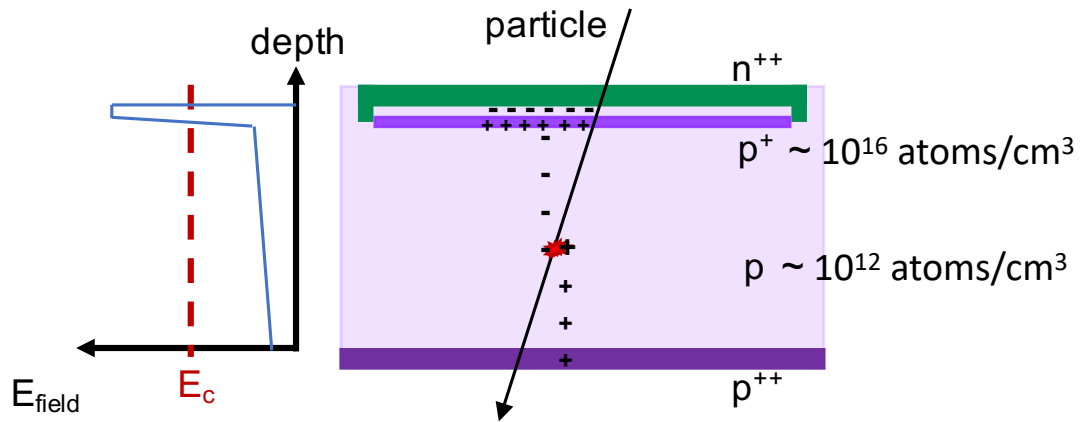
[S. Meroli et al., [doi:10.1088/1748-0221/6/06/P06013](https://doi.org/10.1088/1748-0221/6/06/P06013)]

Low-Gain Avalanche Diodes (LGADs) provide a controlled internal multiplication of signal

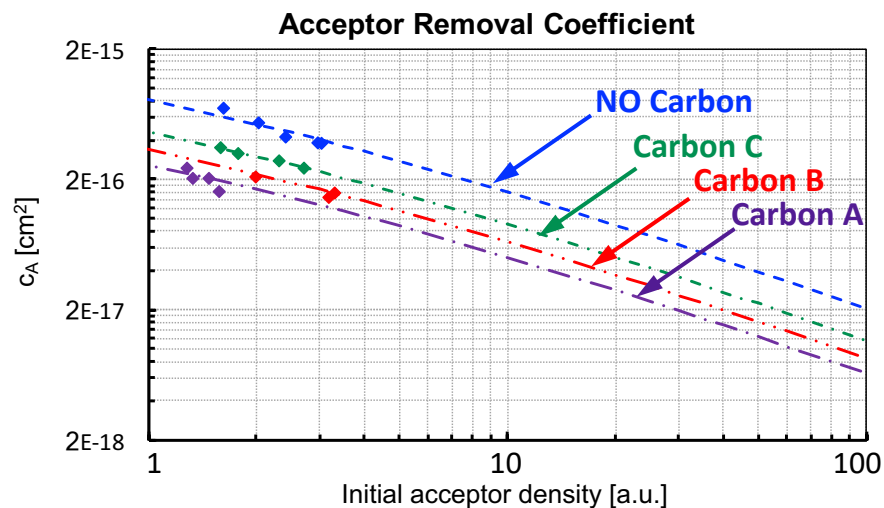
→ E_{field} above E_c for short distance well controlled by V_{bias}

⇒ **Need a gain of at least 5 – 10**
to efficiently record a hit

Low-Gain Avalanche Diodes & Irradiation



LGADs are n-in-p silicon sensors
 Operated in low-gain regime (20–30) controlled by the external bias
 Critical electric field $\sim 20\text{--}30\text{ V}/\mu\text{m}$



The acceptor removal mechanism deactivates the p^+ -doping of the **gain layer** with irradiation according to

$$p^+(\Phi) = p^+(0) \cdot e^{-c_A \Phi}$$

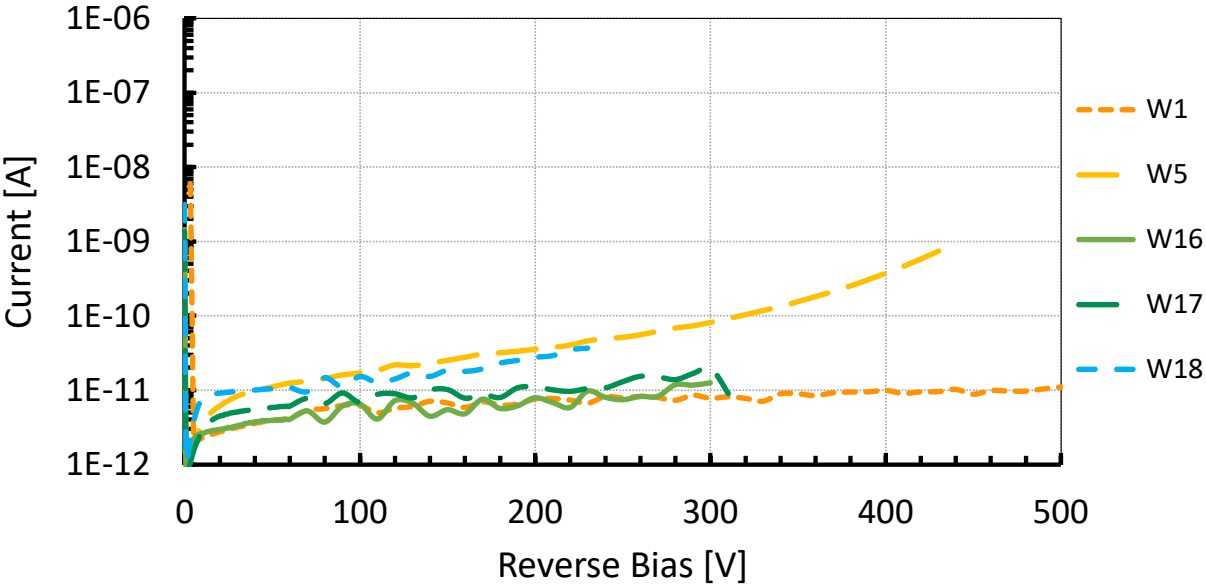
where c_A is the acceptor removal coefficient
 c_A depends on the initial acceptor density, $p^+(0)$, and on the defect engineering of the gain layer atoms

[M. Ferrero et al., [doi:10.1016/j.nima.2018.11.121](https://doi.org/10.1016/j.nima.2018.11.121)]

Standard LGAD – I-V at Different Thickness

Wafer #	Thickness	p+ dose	C dose	Diffusion
1	45	1.04	1.0	CBL
5	30	1.02	1.0	CBL
16	20	0.80	1.0	CHBL
17	20	0.86	1.0	CBL
18	15	0.84	1.0	CBL

EXFLU1 – PIN vs Thickness – I-V

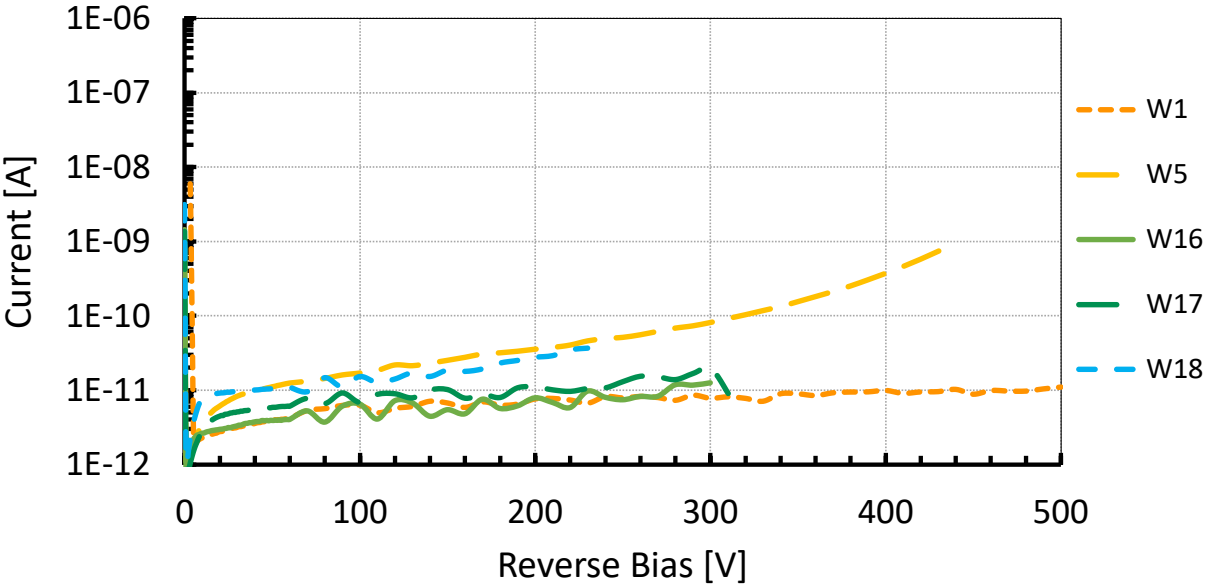


Standard LGAD – I-V at Different Thickness

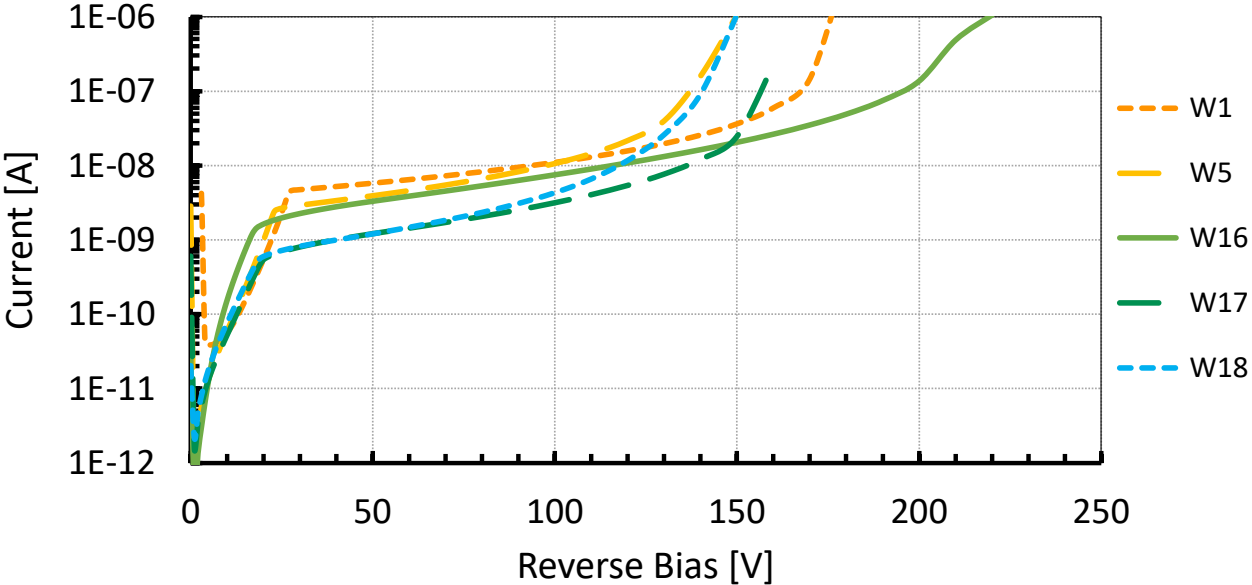
Wafer #	Thickness	p+ dose	C dose	Diffusion
1	45	1.04	1.0	CBL
5	30	1.02	1.0	CBL
16	20	0.80	1.0	CHBL
17	20	0.86	1.0	CBL
18	15	0.84	1.0	CBL

In LGAD sensors, the breakdown due to gain occurs between 150 and 220 V

EXFLU1 – PIN vs Thickness – I-V

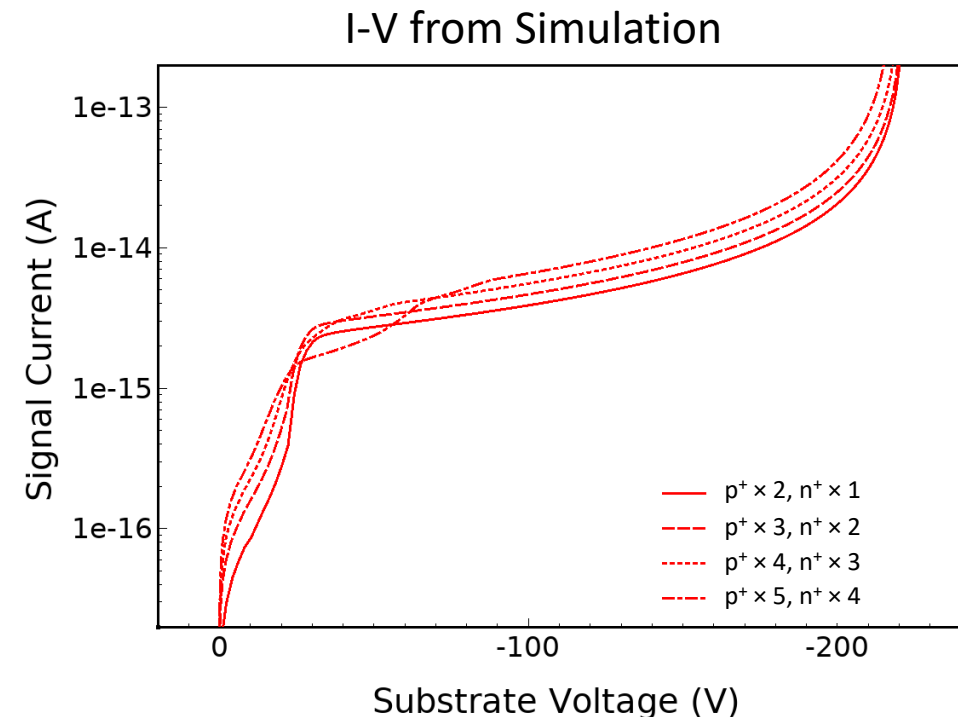
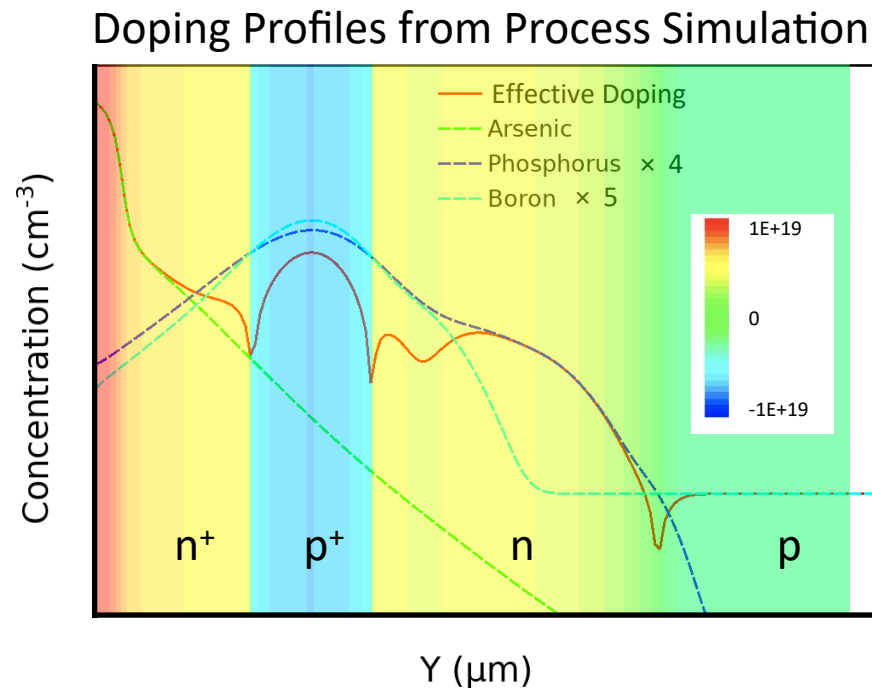


EXFLU1 – Standard LGAD vs Thickness – I-V



Compensation – Simulation & Design

Process simulations of Boron (p^+) and Phosphorus (n^+) implantation and activation reveal the different shape of the two profiles (TCAD Silvaco)



→ The simulation of the electrostatic behaviour show that it is possible to reach similar multiplication for different values of initial compensation (TCAD Synopsys)

Compensation – Doping Evolution with Fluence

Three scenarios of net doping evolution with fluence are possible, according to the acceptor and donor removal interplay :

1. $c_A \sim c_D$

p^+ & n^+ difference will remain constant \Rightarrow unchanged gain with irradiation

\rightarrow **This is the best possible outcome**

2. $c_A > c_D$

effective doping disappearance is slower than in the standard design

\rightarrow **Co-implantation of Carbon** atoms mitigates the removal of p^+ -doping

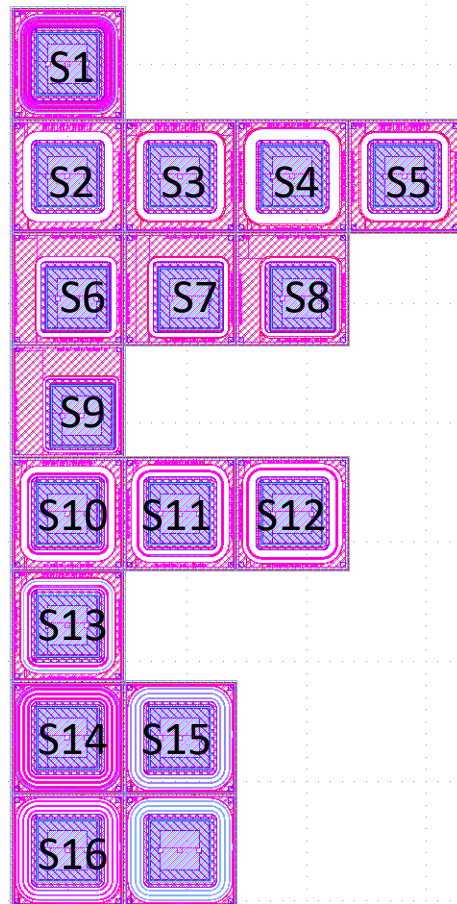
3. $c_A < c_D$

n^+ -atoms removal is faster \Rightarrow increase of the gain with irradiation

\rightarrow **Co-implantation of Oxygen** atoms might mitigate the removal of n^+ -doping

Guard Ring Design Optimised for Thin Sensors

16 different guard rings have been designed, optimised for thin substrates and extreme fluences



3 different guard ring strategies:

▷ 0 GR floating, varying the edge size

– different size of the ‘empty’ region

– different size of the edge region: 500, 300 & 200 μm

▷ 1 GR floating, varying the GR position

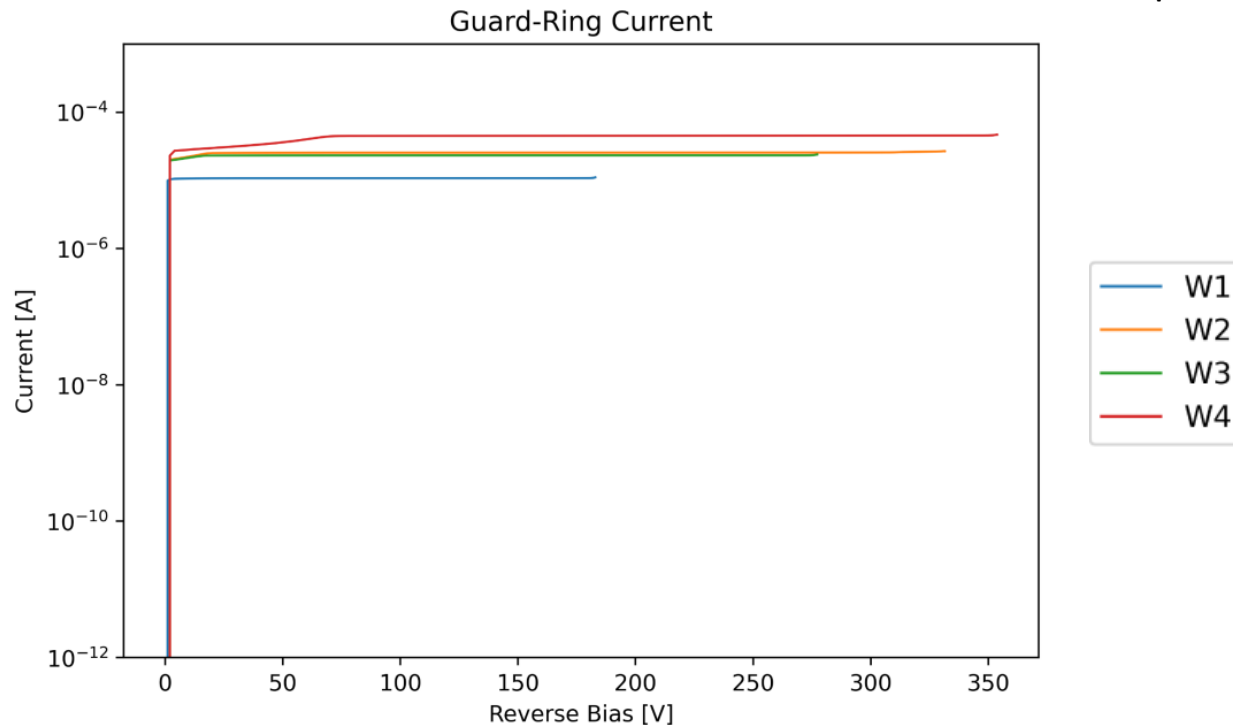
▷ 3 GR floating with different designs

[S1 is the standard design used in previous UFSD batches]

Optimised Guard Ring Design on 45 μm

45 μm substrates converted to n-type

EXFLU1 – 45 μm LGAD

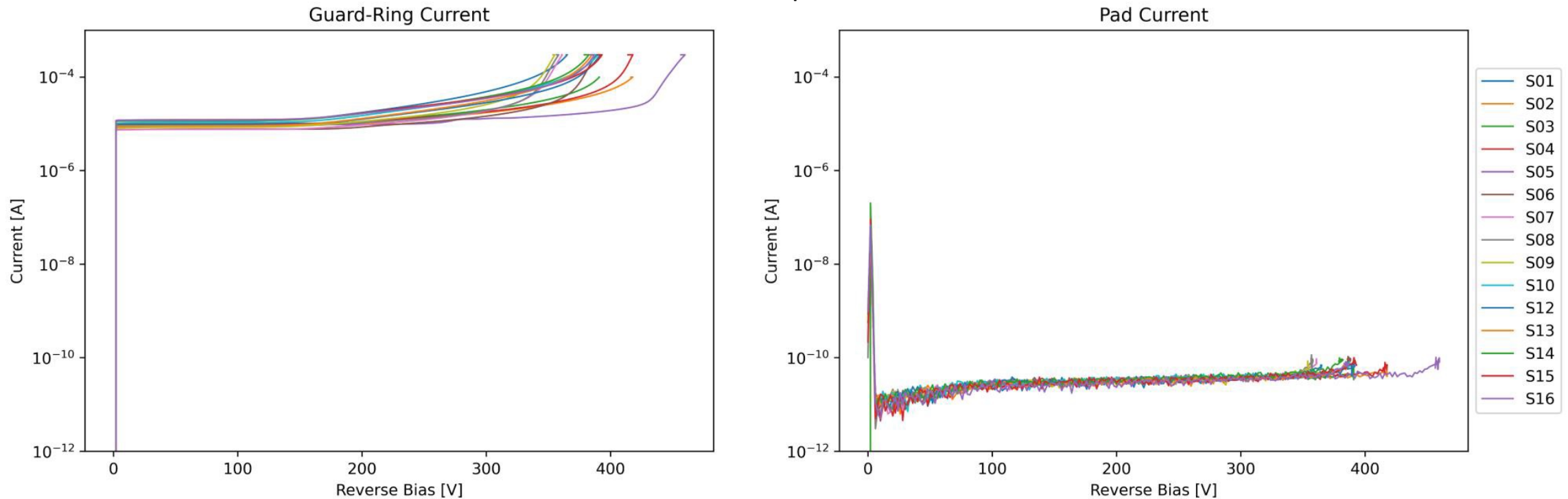


→ Due to the substrate doping, the guard ring current is high and almost constant

Optimised Guard Ring Design on 45 μm

45 μm substrates converted to n-type

EXFLU1 – 45 μm PIN



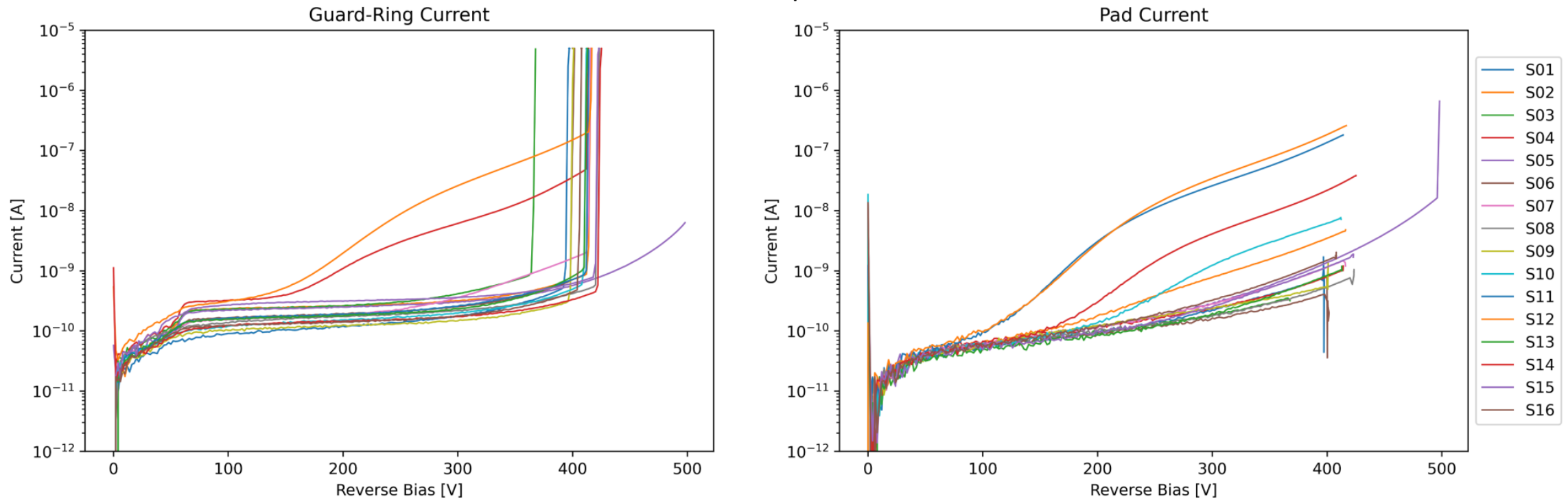
→ Due to the substrate doping, the guard ring current increases above 350 V

→ Current on the pad is small

Optimised Guard Ring Design on 30 μm

30 μm substrates have a resistivity of $\sim 900 \Omega\cdot\text{cm}$

EXFLU1 – 30 μm PIN

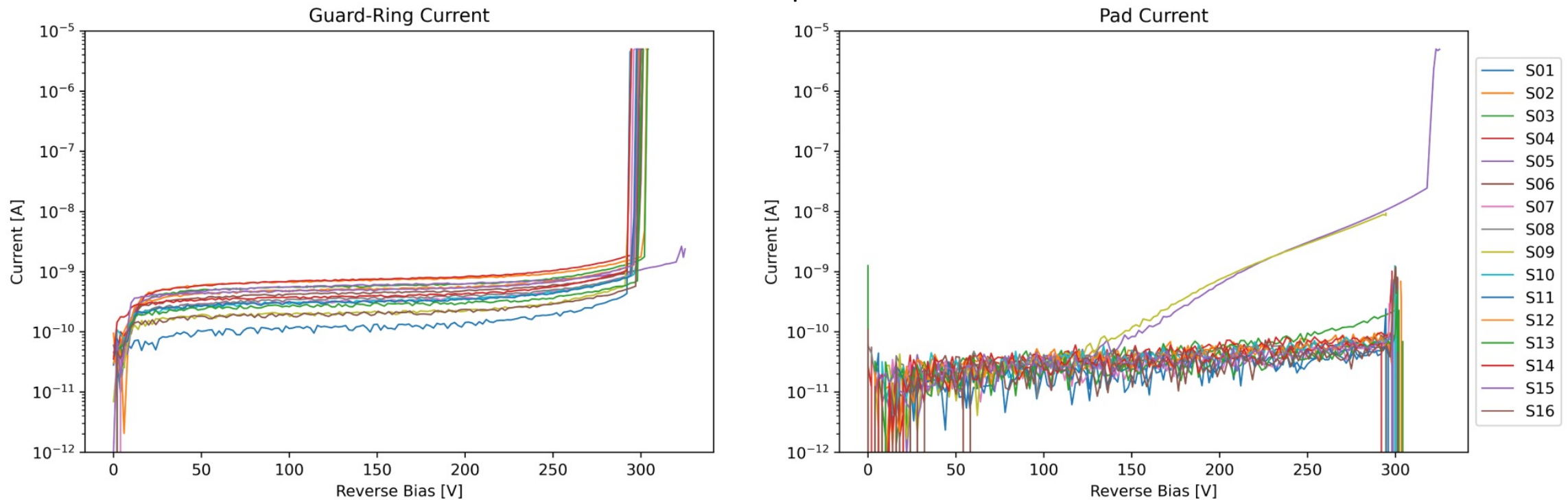


- Most of the guard rings exhibit a breakdown at $\sim 400 \text{ V}$ ($E_{\text{field}} \sim 14 \text{ V}/\mu\text{m}$), except S5
- High current observed on guard rings and pads may be due to defects in the substrate

Optimised Guard Ring Design on 20 μm

20 μm substrates have a resistivity of $\sim 90 \Omega\cdot\text{cm}$

EXFLU1 – 20 μm PIN



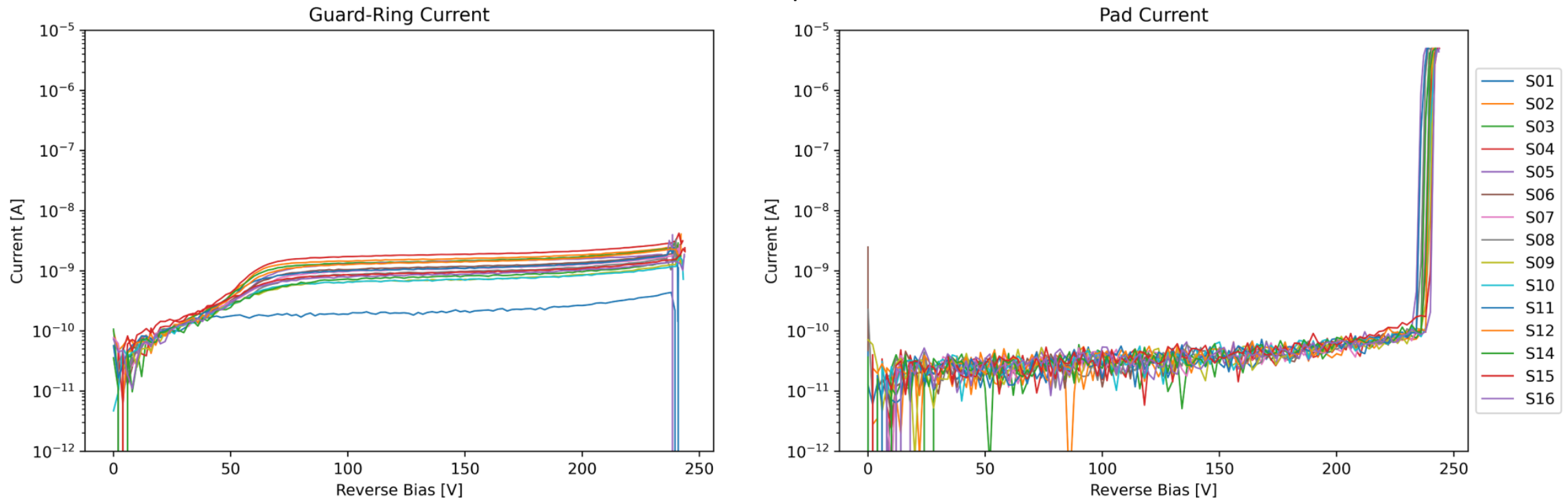
→ Most of the guard rings exhibit a breakdown at $\sim 300 \text{ V}$ ($E_{\text{field}} \sim 15 \text{ V}/\mu\text{m}$), except S5

→ S5 design (zero floating guard rings) reaches breakdown in the pad

Optimised Guard Ring Design on 15 μm

15 μm substrates have a resistivity of $\sim 90 \Omega\cdot\text{cm}$

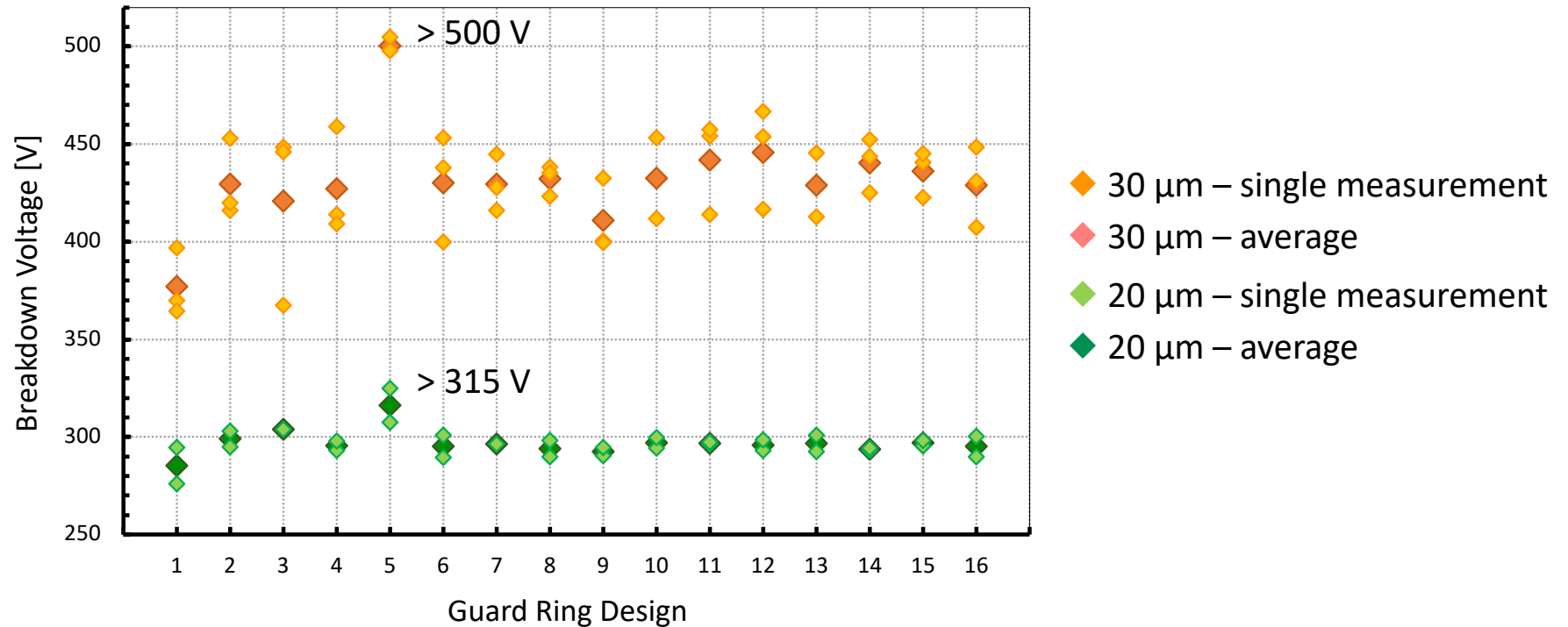
EXFLU1 – 15 μm PIN



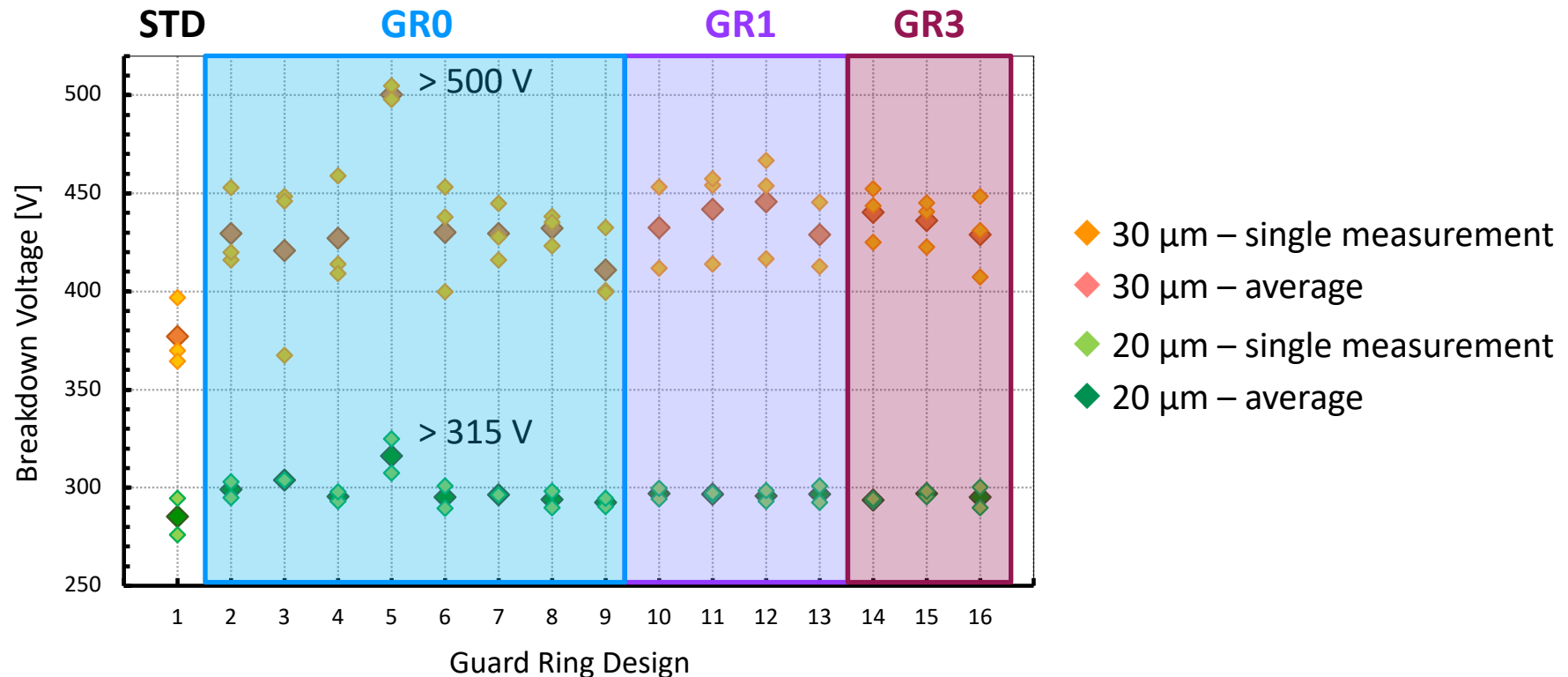
→ No breakdown on guard rings is observed up to 240 V ($E_{\text{field}} \sim 16 \text{ V}/\mu\text{m}$)

→ In 15 μm thick sensors, breakdown is reached in the pad

Optimised Guard Ring Design – Summary



Optimised Guard Ring Design – Summary



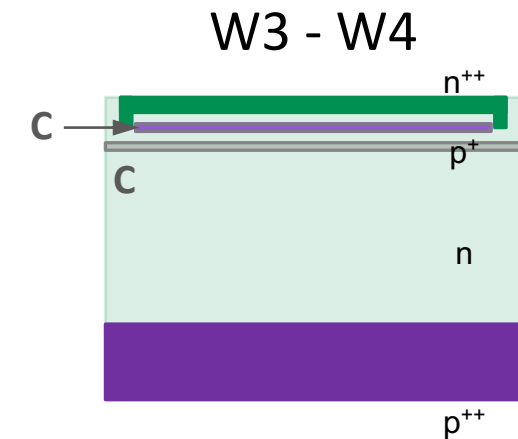
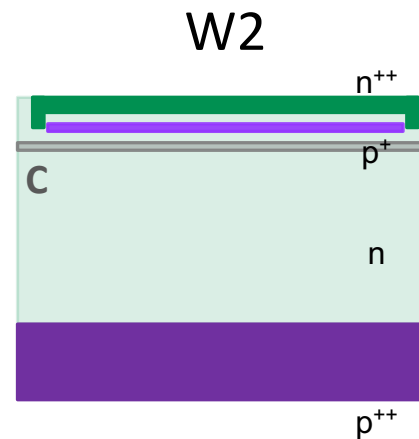
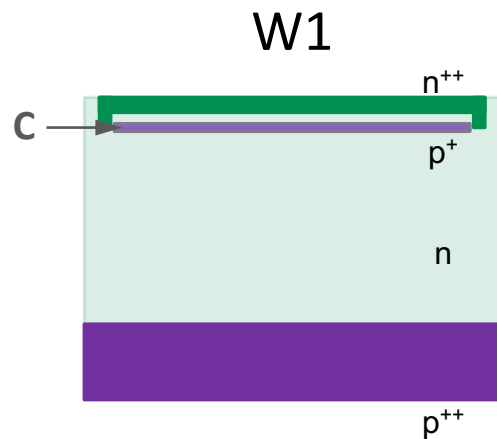
- 30 μm thick sensors show a bigger variation in the breakdown voltage wrt 20 μm thick ones
- All guard ring designs are working properly and ensure good operation of the sensors
- An extensive irradiation campaign will be performed to study the radiation tolerance of each design

Standard LGAD with Carbon Shield



Wafer #	Thickness	p+ dose	C dose	C shield	Diffusion
1	45	1.04	1.0		CBL
2	45	1.00		0.6	CBL
3	45	1.06	1.0	0.6	CBL
4	45	1.06	1.0	1.0	CBL

NB: the bulk of the 45 μm substrates swapped into n-type



Production costs increase by $\sim 20\%$

→ Expected improvement in radiation tolerance of 20 – 30%

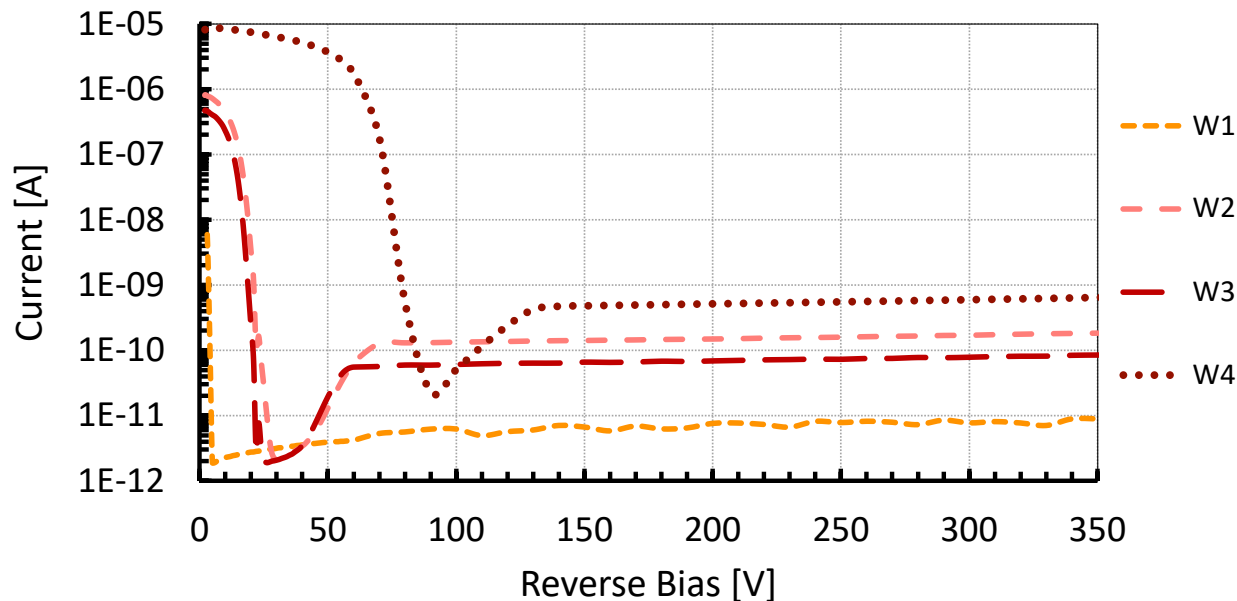
Standard LGAD – I-V with Carbon Shield



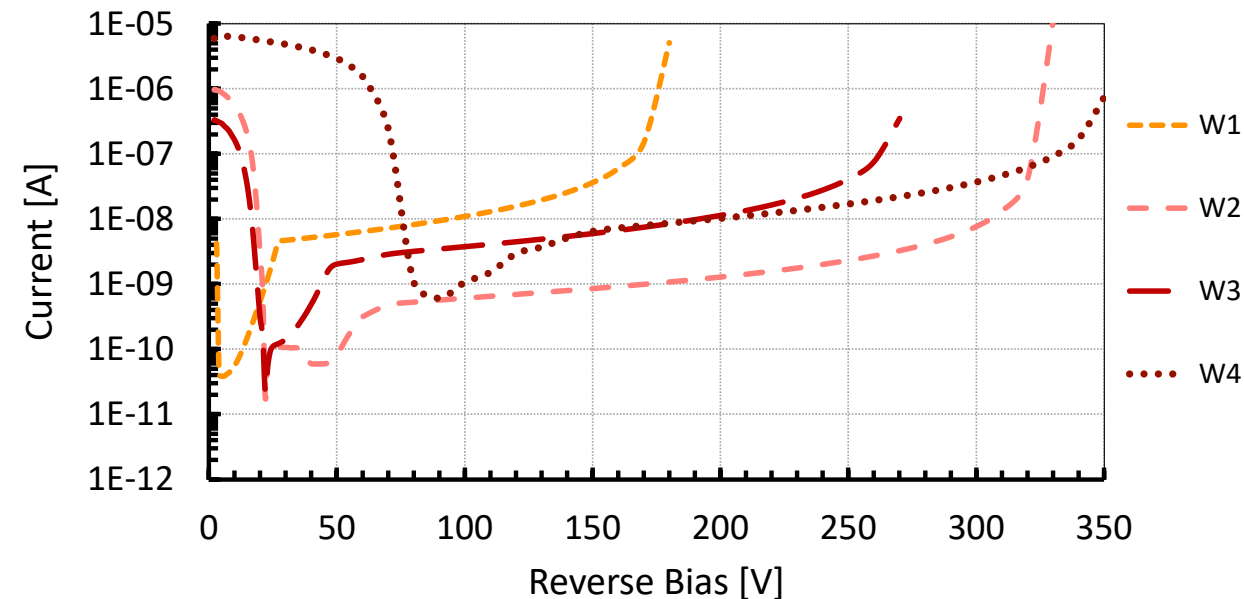
Wafer #	Thickness	p+ dose	C dose	C shield	Diffusion
1	45	1.04	1.0		CBL
2	45	1.00		0.6	CBL
3	45	1.06	1.0	0.6	CBL
4	45	1.06	1.0	1.0	CBL

Carbon shield shifts the breakdown voltage to higher values of bias

EXFLU1 – PIN with C shield – I-V



EXFLU1 – Standard LGAD with C shield – I-V



Evolution of the Donor Removal

A further production batch is needed to study the donor removal

Evolution of donor density: $N_{\text{eff}}(\Phi) = N_D(0)e^{-c_D \cdot \Phi} - g_c \cdot \Phi$

State-of-the-art [M.Moll et al., [doi:10.1016/S0168-9002\(99\)00842-6](https://doi.org/10.1016/S0168-9002(99)00842-6)]

We need to study donor removal in a range $10^{16} - 10^{18}$ atoms/cm³

NB: Oxygen has for donor removal a very similar effect of Carbon to acceptor removal

Silicon Sensor for Extreme Fluences (eXFlu) project – V. Sola as PI

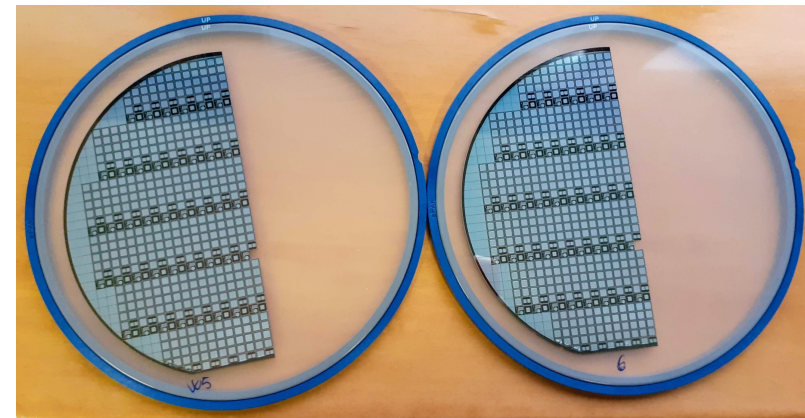
In 2020, INFN awarded for funding a 2 years grant for young researchers to **develop, produce, irradiate and study thin silicon sensors**

Thin LGAD wafers have been produced at FBK

→ **EXFLU0 production**

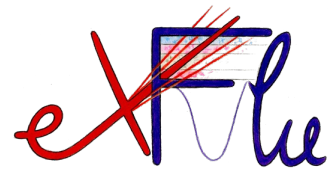
- ▷ 2 different wafer thicknesses: **25 & 35 μm**
- ▷ epitaxial substrates
- ▷ **single pads** and 2x2 arrays

Arrived in Torino at the end of 2020

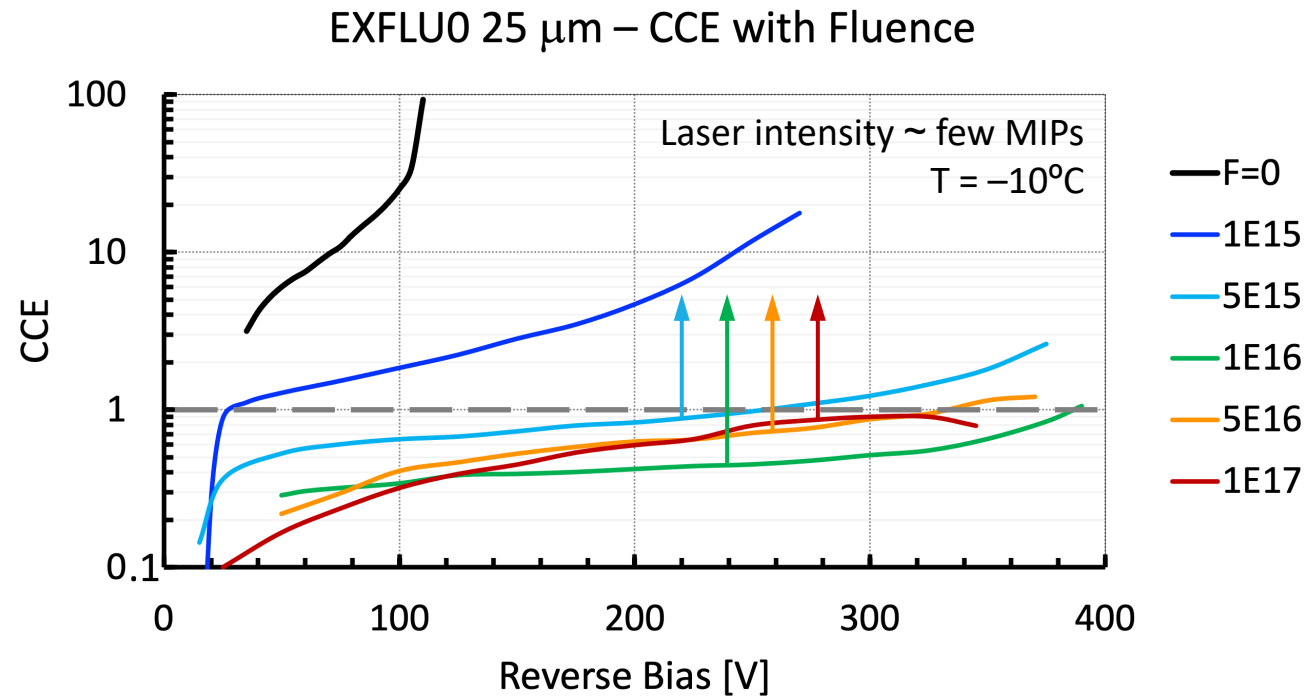


EXFLU0 sensors have been irradiated at JSI, Ljubljana, to 5 different fluences 1E15, 5E15, 1E16, 5E16, 1E17 $n_{\text{eq}}/\text{cm}^2$

25 μm LGAD Signal at Different Fluences



Measurements of charge collection efficiency (CCE) with an infra-red laser stimulus show that sensors can be operated up to the highest fluences



- ▷ The LGAD multiplication mechanism ceases existing at $\sim 5 \cdot 10^{15} \text{ cm}^{-2}$
- ▷ From 10^{16} to 10^{17} cm^{-2} the collected signal is roughly constant
- ▷ At high bias the signal increases due to internal gain, but does not reach the minimum charge required by the electronics

→ **Necessary to increase the radiation tolerance of the gain mechanism above 10^{15} cm^{-2}**

Involved Partners – INFN TO

- ▷ The Torino Unit of the Istituto Nazionale di Fisica Nucleare (INFN) will
 - coordinate the project and organise the activities
 - follow the sensor design and production processes
 - characterisation and test of the sensors
 - organise of the irradiation campaign
 - provide the input to the simulation and modelling process

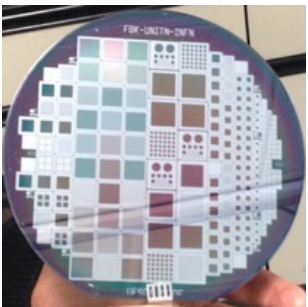


⇒ Well-established tradition in the development of Low-Gain Avalanche Diodes since the early stage

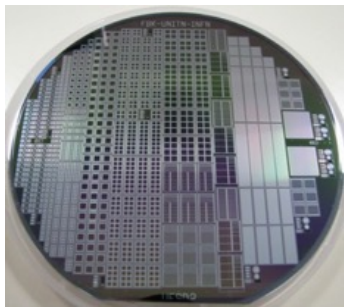
Involved Partners – FBK

- ▷ Fondazione Bruno Kessler (FBK) will
 - define the optimal process flow for the two sensor production
 - take care of the **sensors fabrication process**
 - provide the first sensor characterisation at the foundry

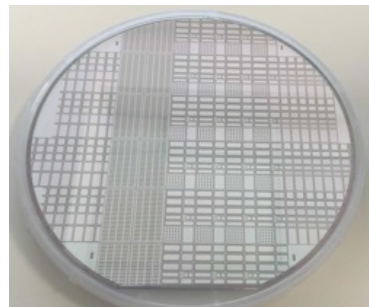
Previous LGAD productions at FBK (not-exhaustive list)



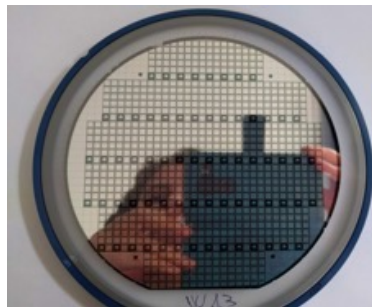
UFSD1
2016



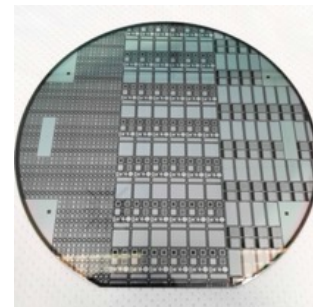
UFSD2
2017



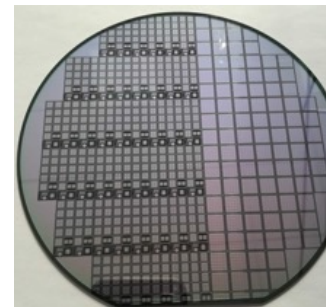
UFSD3
2018



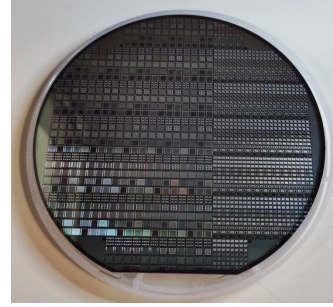
UFSD3.1
2019



RSD1
2019



UFSD3.2 + EXFLU0
2020



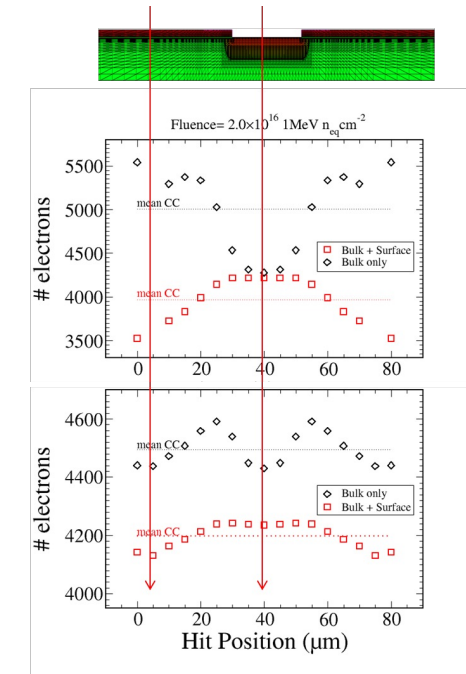
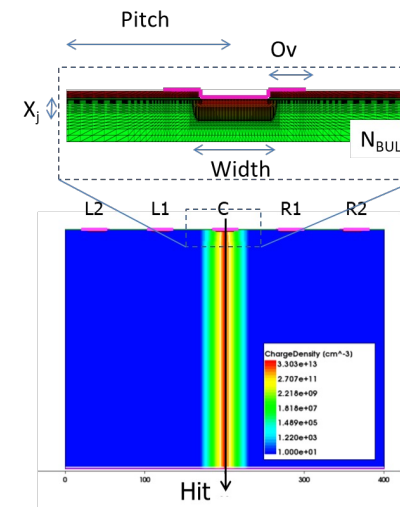
TI-LGAD
2021

⇒ FBK will bring its strong expertise in the design and production of silicon sensors with internal gain, now considered at the state-of-the-art by the scientific community.

Involved Partners – INFN Pg

- The Perugia Unit of the Istituto Nazionale di Fisica Nucleare (INFN) will
 - provide simulation of the sensor behaviour to drive the production processes
 - participate to the sensor characterisation and testing
 - implement the observations into the model
 - extend the sensor modelling to unexplored regions of fluence

MPI TS2000 SE
Semi-automatic probe station
Triaxial thermal chuck $-60^{\circ}\text{C} \div +200^{\circ}\text{C}$



⇒ INFN Pg contribute to the project bringing its experience in the interpretation and modelling of silicon damage through the development and application of Technology CAD tools

Possible Fields of Interest

- **Silicon-based tracker detectors at future high-energy and high-intensity hadron colliders**, where the expected radiation budget at those machines is above $1\text{E}16\text{ cm}^{-2}$ in the outermost part of the tracking region and up to $1\text{E}18\text{ cm}^{-2}$ close to the interaction point.
- **Beam monitor for particle therapy facility**, as cancer treatment effectiveness strongly relates to the accuracy of real-time monitoring of the beam intensity and profile to optimise the dose delivery to the cancer tissue, the patient safety, and the operation of the accelerating machine. Particle therapy will significantly benefit from silicon-based monitors that can operate for about one year of patient's treatments ($\sim 1\text{E}17\text{ cm}^{-2}$) without being replaced.
- **Monitors at the thermonuclear fusion reactors under development**. In such an environment, with high neutron and g fluxes, X-ray monitors are crucial to ensure safe operations, control of the nuclear plasma, and precise evaluation of physics phenomena.